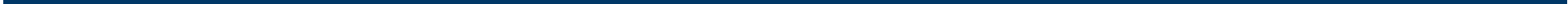


# Advanced CCD and CMOS Image Sensor Technology at MIT Lincoln Laboratory

Vyshnavi Suntharalingam  
American Physical Society March Meeting

27 February 2012

 **LINCOLN LABORATORY**  
MASSACHUSETTS INSTITUTE OF TECHNOLOGY

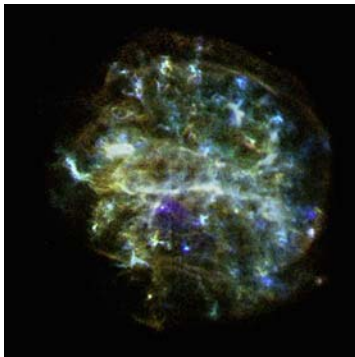
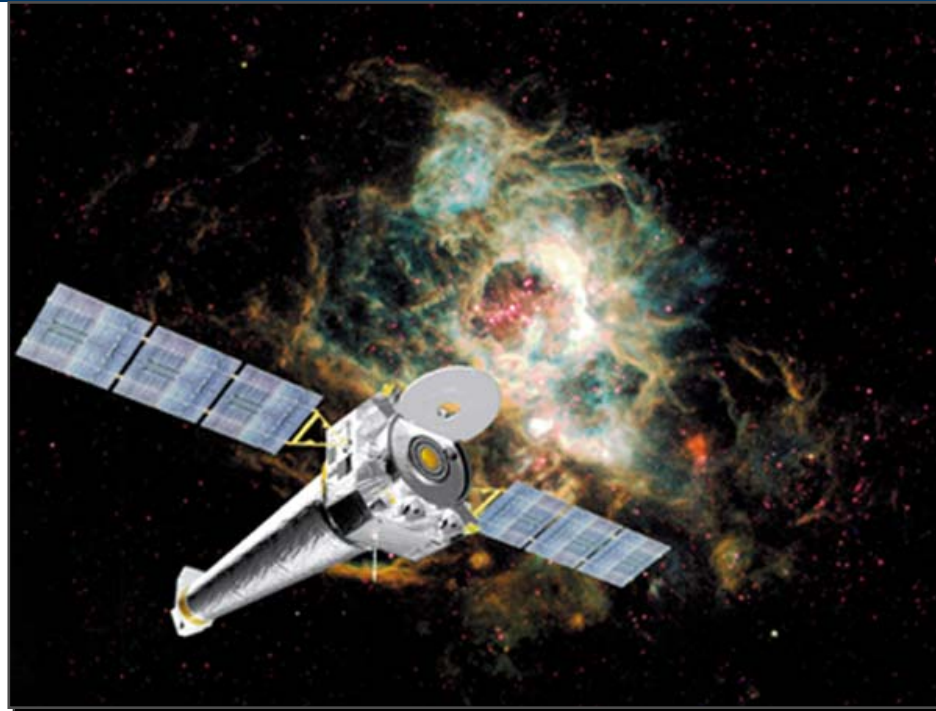






# NASA Chandra X-ray Great Observatory

## Launched July 1999



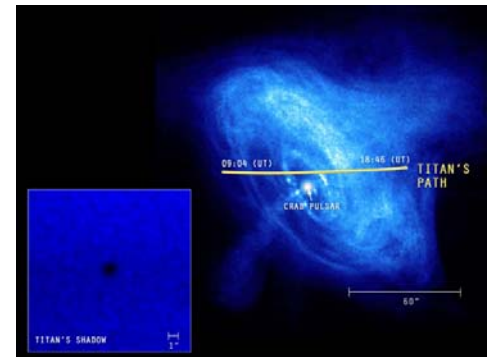
G292.0+1.8



Centaurus A



PSR B1509-58



Titan's shadow

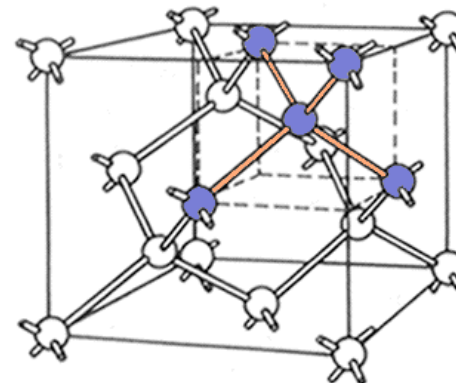




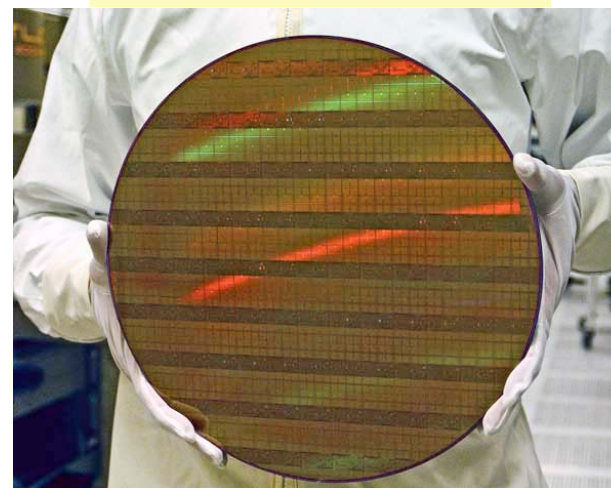
# The Silicon Advantage

- **Abundant**
- **Elemental semiconductor**
- **Can be highly purified (<ppb)**
  - **Controlled amount of impurities can be added**
- **Forms strong covalent bonds with itself and with Oxygen**
  - **High melting point**
    - **c-Si: 1440°C; SiO<sub>2</sub>: 1700°C**
  - **SiO<sub>2</sub> can be used for isolation and protection**
- **Can combine with halogens and hydrogen if there is no oxygen**

**Face-Centered Cubic  
Diamond Crystal Lattice**



**300-mm Wafer (Intel)**

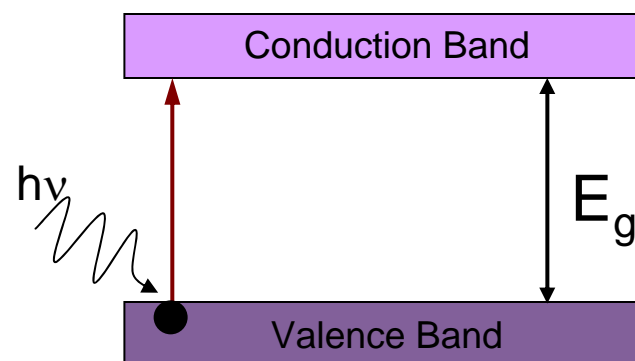




# Photoelectron Creation

- Photons striking the semiconductor excite electrons from the Valence band into the Conduction band
- Absorption occurs for  $h\nu \geq E_g$ 
  - Or  $E_{\text{photon}} = hc/\lambda \geq E_g$

## Intrinsic Semiconductor



Symbol	$E_g$ (eV)	$\lambda_c$ ( $\mu\text{m}$ )
Si	1.12	1.1
InGaAs	0.73 - 0.48	1.68* - 2.6
HgCdTe	1.00 - 0.07	1.24 - 18
InSb	0.23	5.5
Si:As	0.05	25

$$\lambda_c = 1.238 / E_g \text{ (eV)}$$

$h$  = Planck's constant

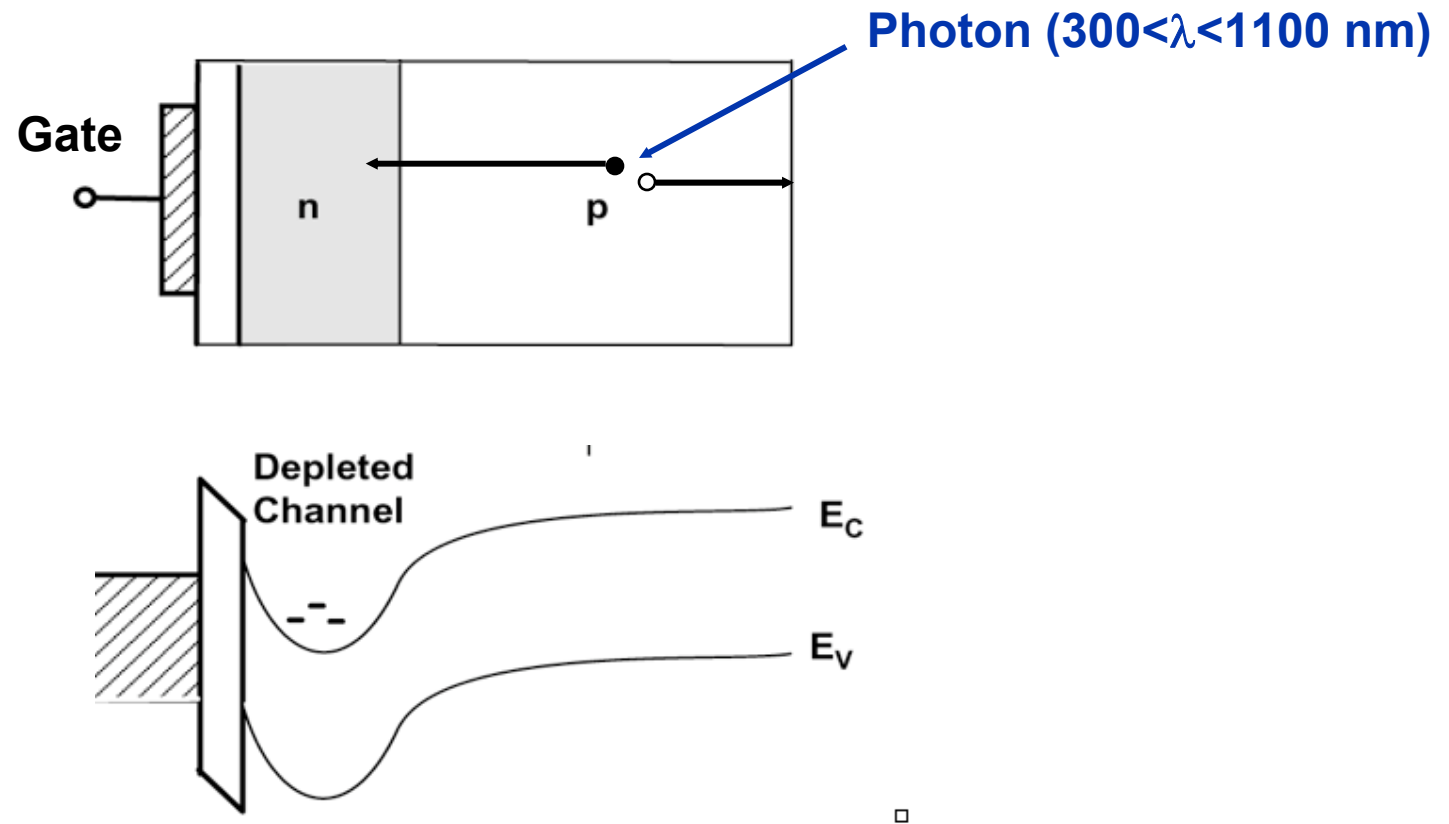
$\nu$  = frequency of light =  $\lambda/c$

$E_g$  = Energy Gap

\*Lattice matched InGaAs ( $\text{In}_{0.53}\text{Ga}_{0.47}\text{As}$ )

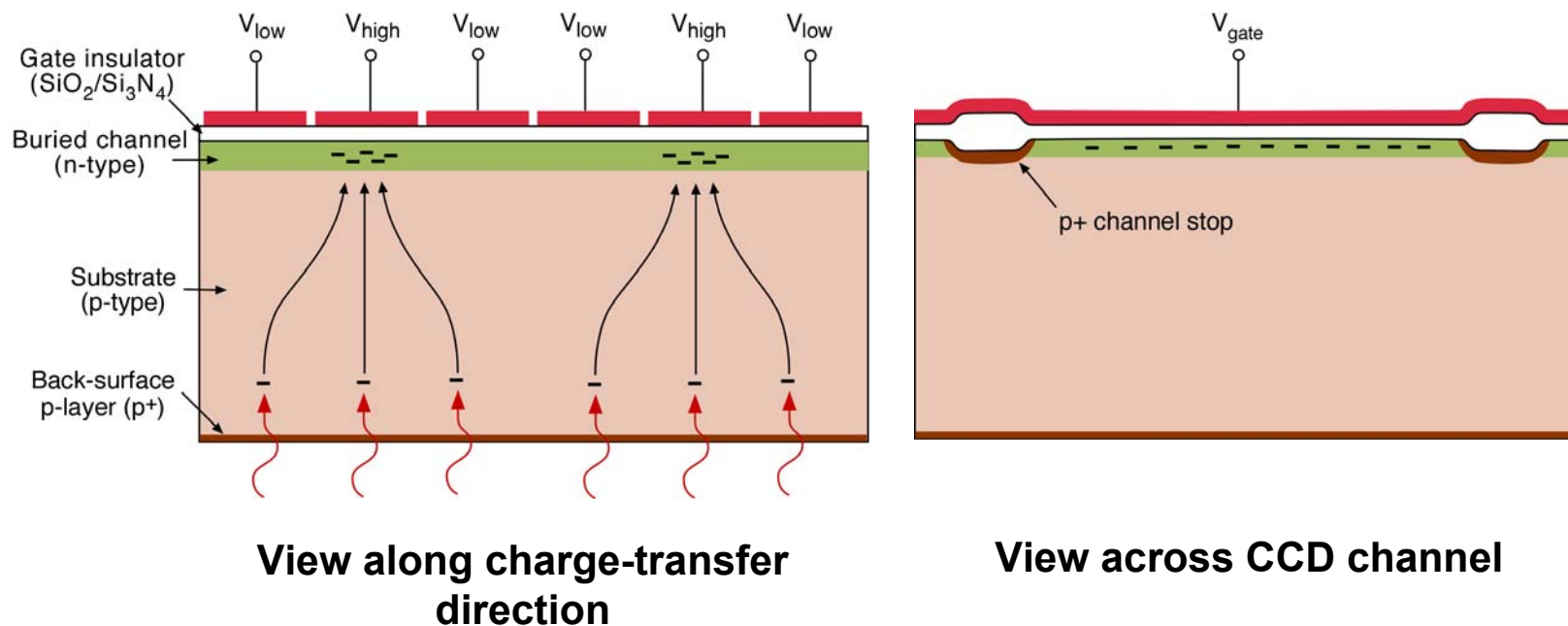


# Detection and Vertical Confinement





# Basic CCD Structure

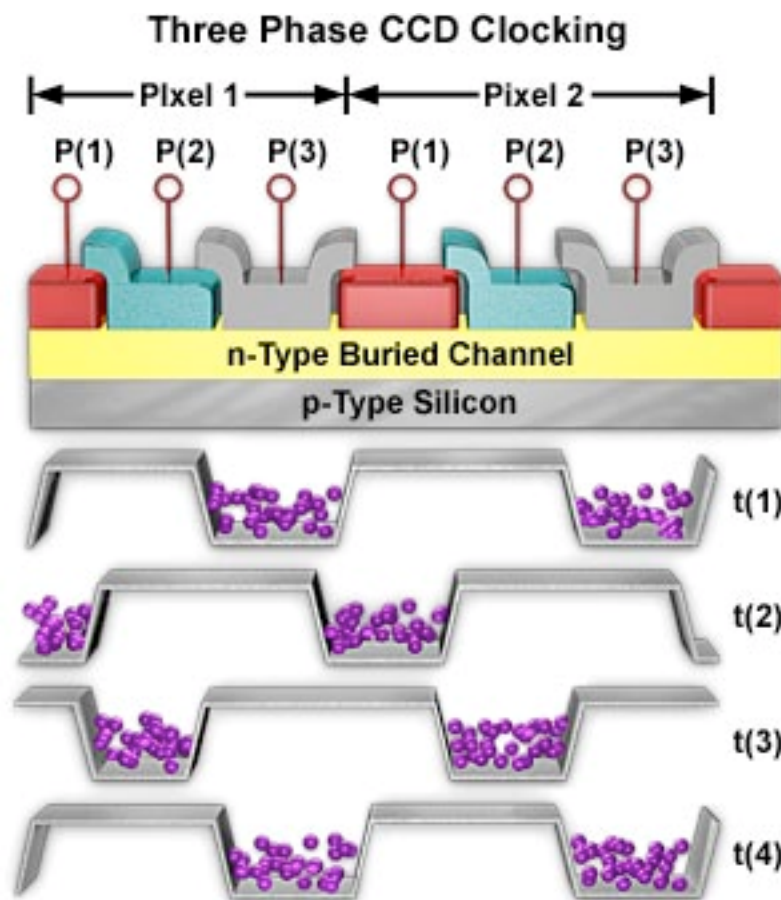






# CCD Operation

Device Cross Section



Potential Distribution

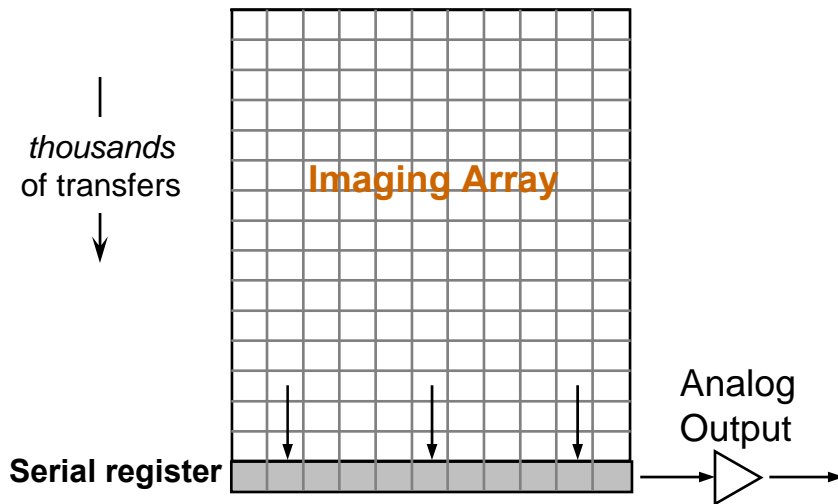
Figure 1

<http://learn.hamamatsu.com/articles/threephase.html>



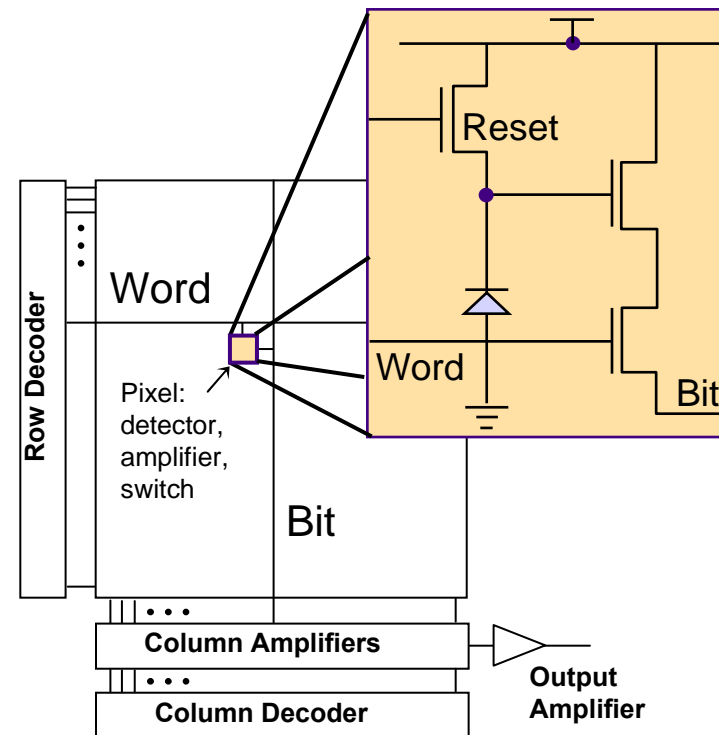
# Comparison of CCD and CMOS Imagers

## CCD imager



- **Pros**
  - Still used in highest performance applications
  - Best QE, lowest noise
- **Cons**
  - Sensitive to proton damage in space applications

## CMOS Active Pixel Sensor (APS)



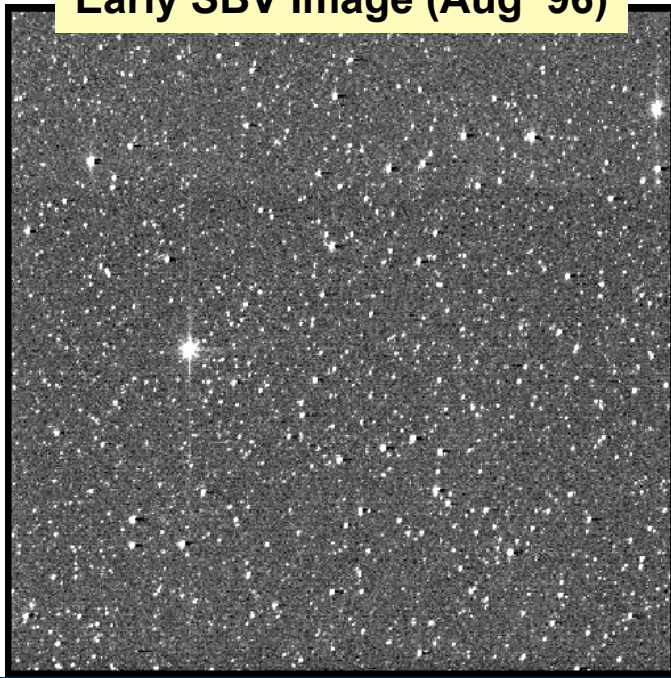
- **Pros**
  - Provides on-chip electronics
- **Cons**
  - Modest imaging performance for monolithic



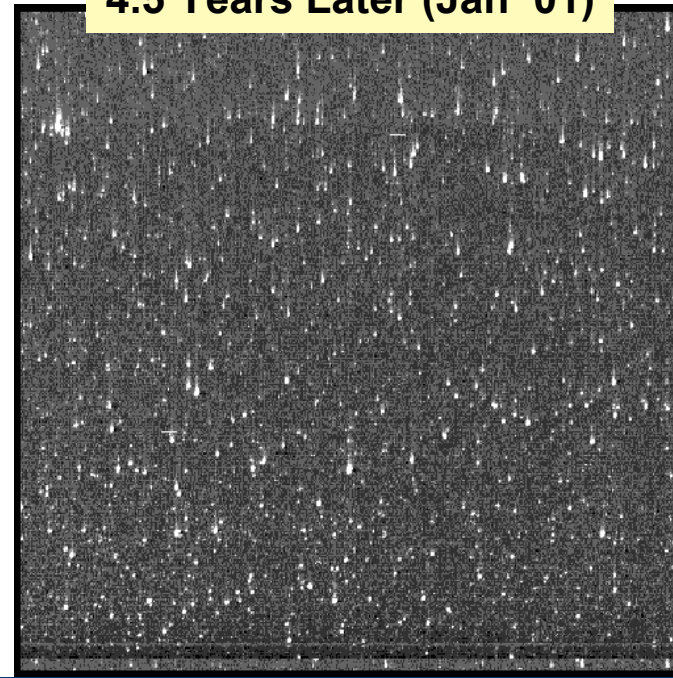
# Effect of Space Environment on CCD Performance: SBV Image Comparison

- Radiation-induced traps in silicon capture electrons during charge transfer and release as trailing charge
- Recent CCD performance improvements
  - Smaller transfer distances
  - Channel engineering
  - Lower temperature
- Better performance with CMOS devices with few/no transfers

Early SBV Image (Aug '96)



4.5 Years Later (Jan '01)

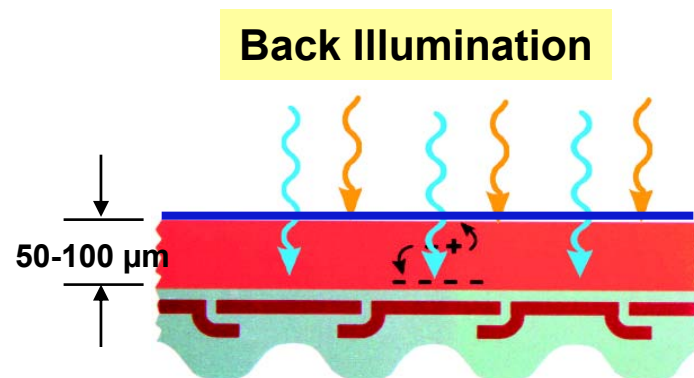
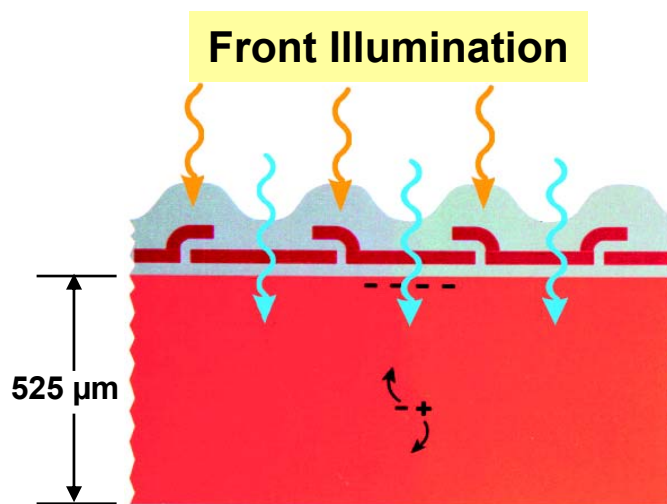


Fabrication 1987



# Back-Illuminated Structure

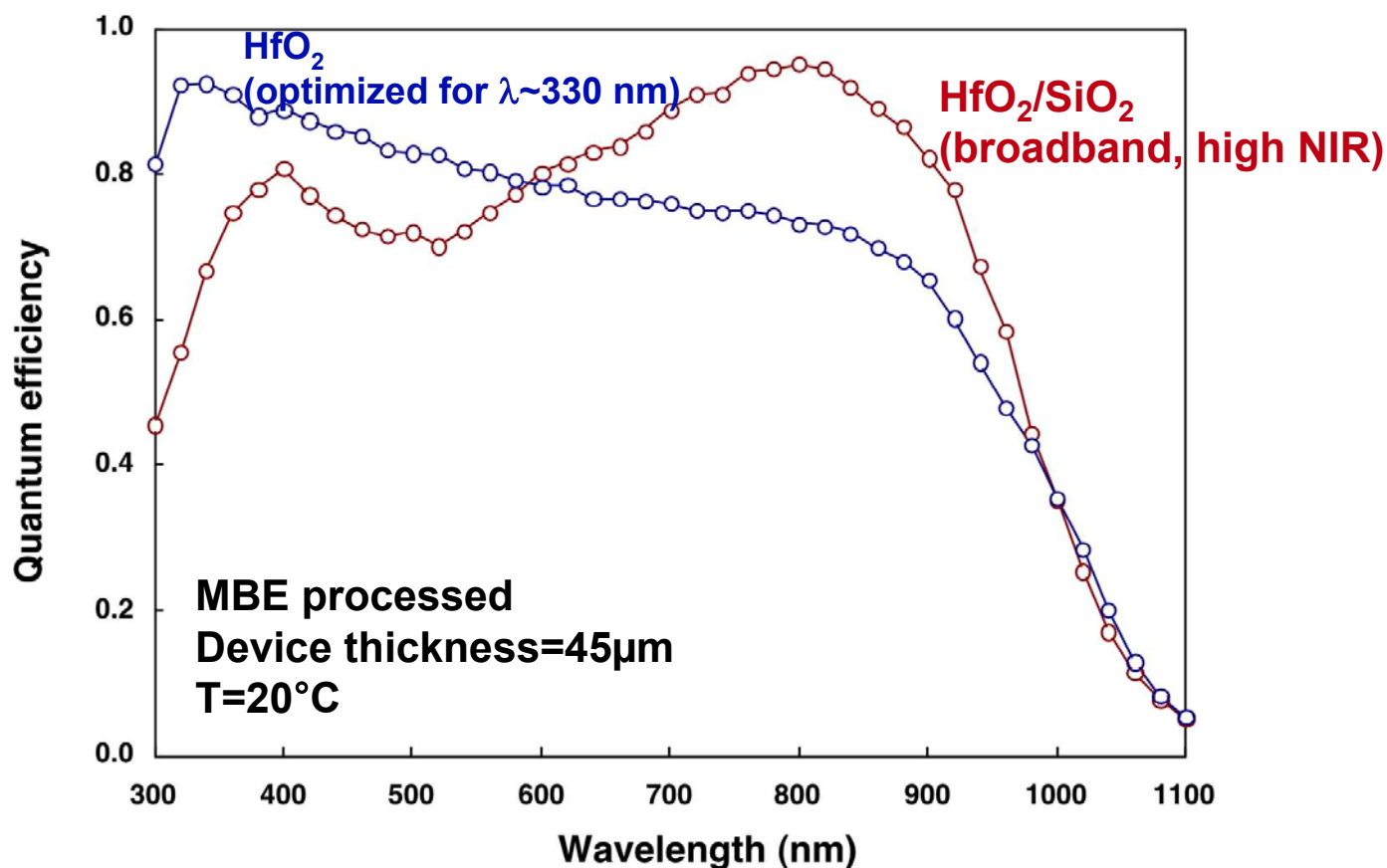
- **Front illumination (FI)**
  - Cheaper to build
  - Absorption in overlying films
  - Reflection losses
- **Back illumination (BI)**
  - More expensive, but becoming more common
  - Direct coupling of photons to active silicon volume
  - AR coatings enable nearly 100% QE
- **Good back-surface treatment required to avoid photoelectron loss**
  - Boron implant and laser anneal
    - e2V, MIT/LL
  - MBE
    - JPL, MIT/LL
  - Chemisorption coating that produces positive charge
    - University of Arizona (Lesser)





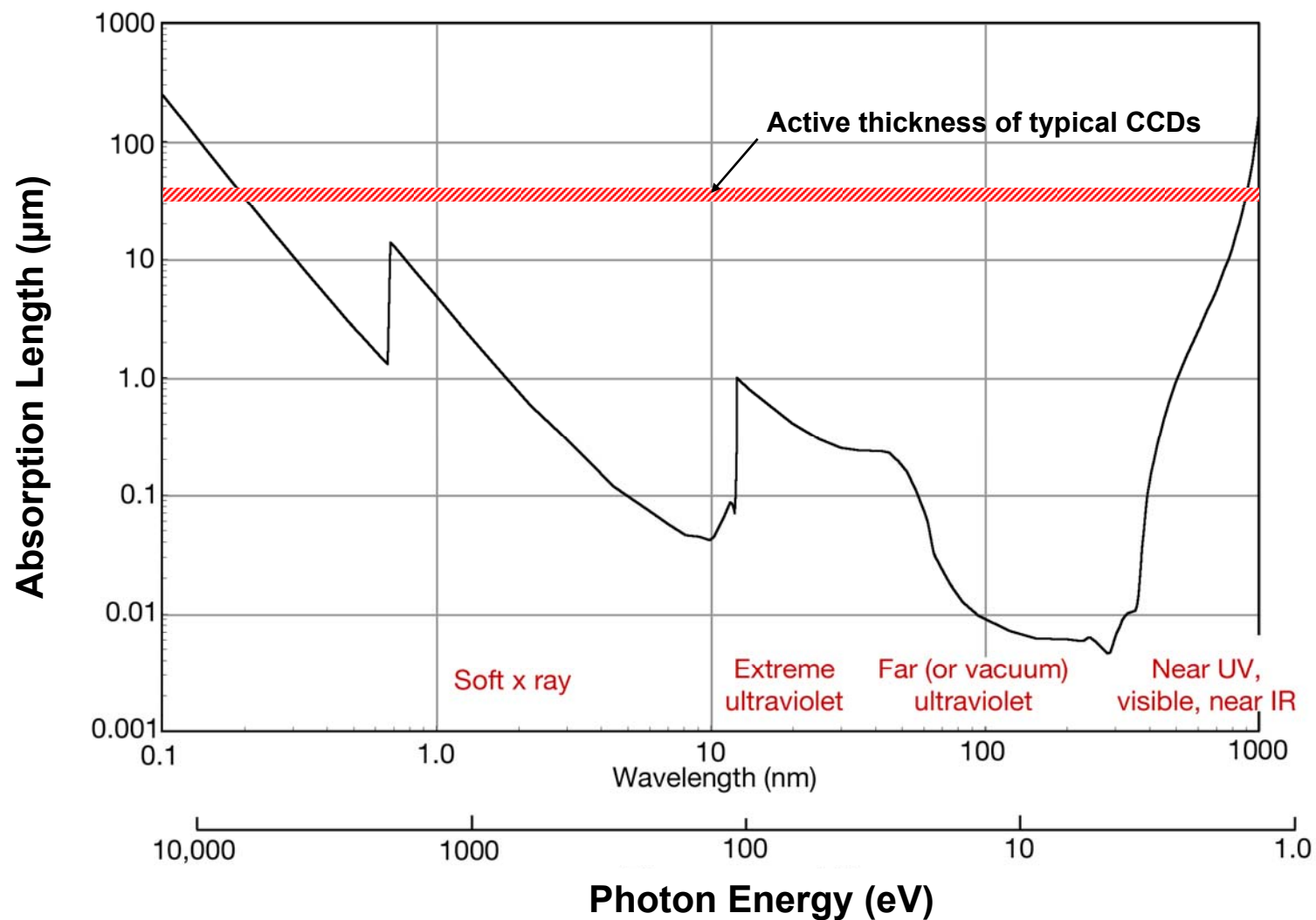
# Anti-Reflection Coatings

- Minimize reflection from air ( $n \approx 1$ ) / silicon ( $n \approx 4$ ) interface
  - Typically Hafnium oxide for single layer ( $\lambda/4$ ) coatings
  - Specialized coatings developed with two layers or graded thicknesses





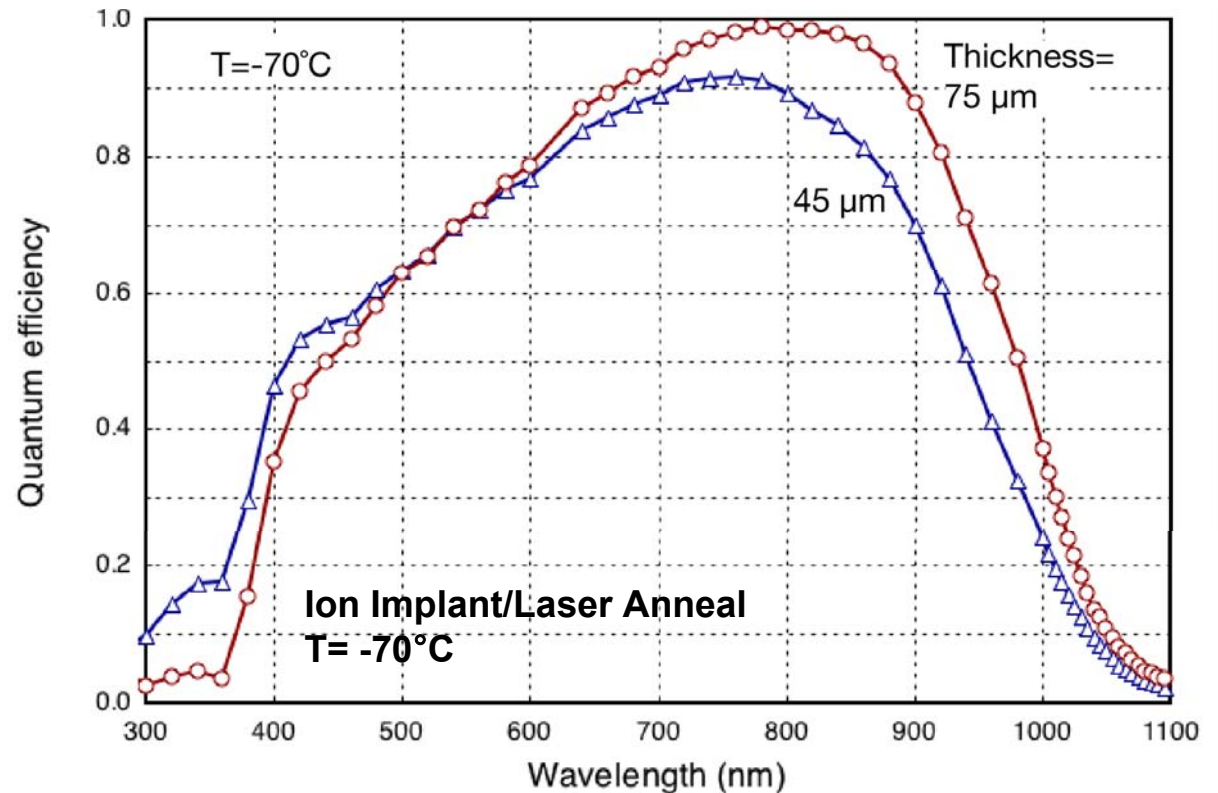
# Photon Absorption Length in Silicon





# Effect of Silicon Thickness on NIR Spectral Response

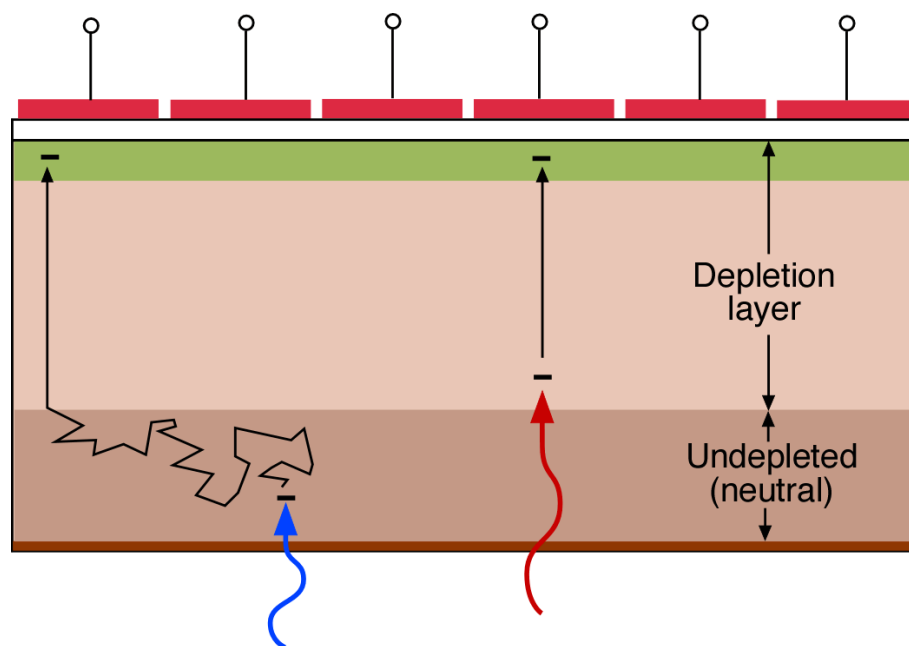
- Near-IR response requires thicker silicon
  - Specialized material with resistivity > 3000 ohm-cm
- Considerations:
  - Increased PSF with large undepleted depth





# Effects of Partial Depletion

- Full depletion essential for minimal charge spreading (high MTF)
- Methods to ensure full depletion
  - Thin device
  - High-resistivity substrate
  - High clock voltages
  - Bias back-surface  $p^+$  negative

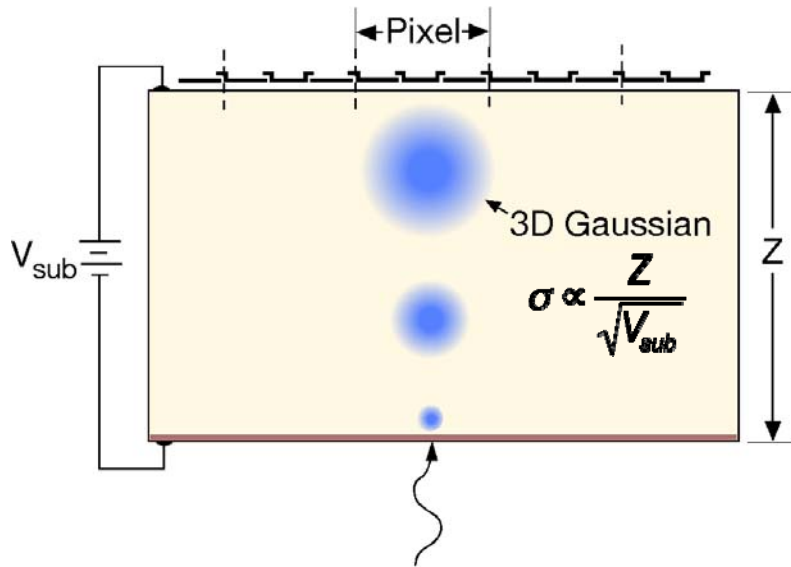




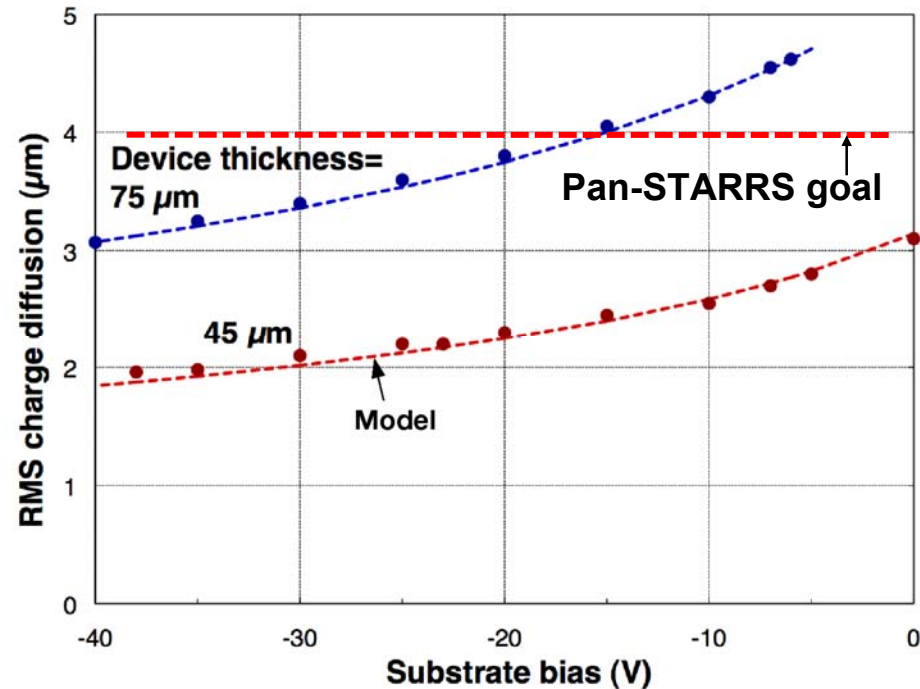


# Tradeoff: High QE vs. Imager Resolution

- Voltage bias across sensor produces high resolution in thick imagers



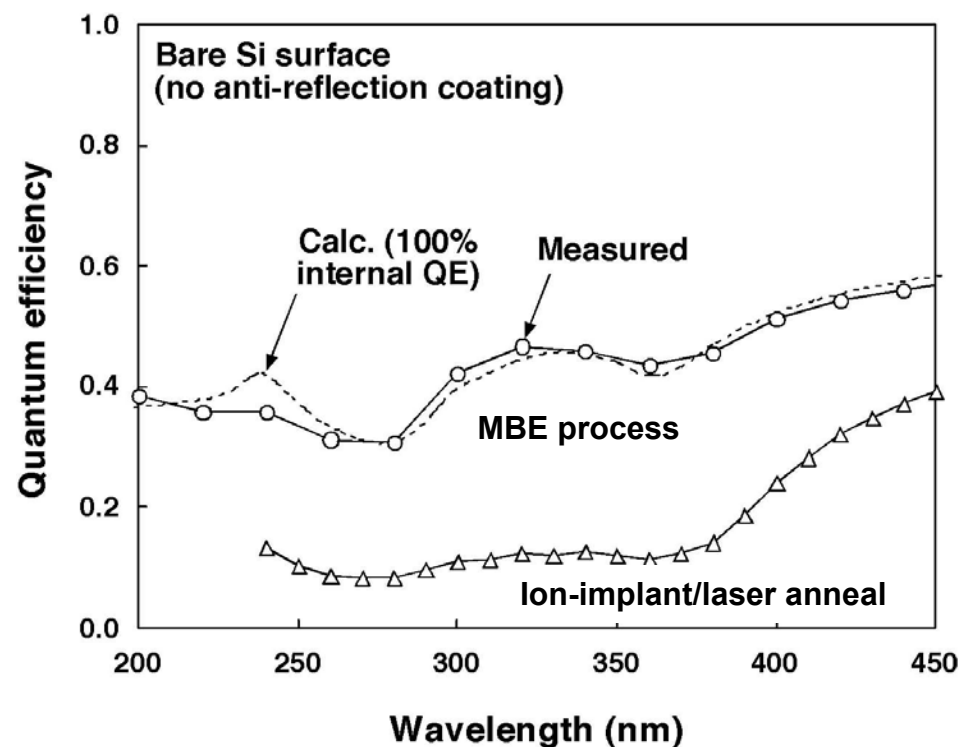
## Measured charge diffusion vs. substrate bias and device thickness





# UV-Sensitive Silicon Detectors

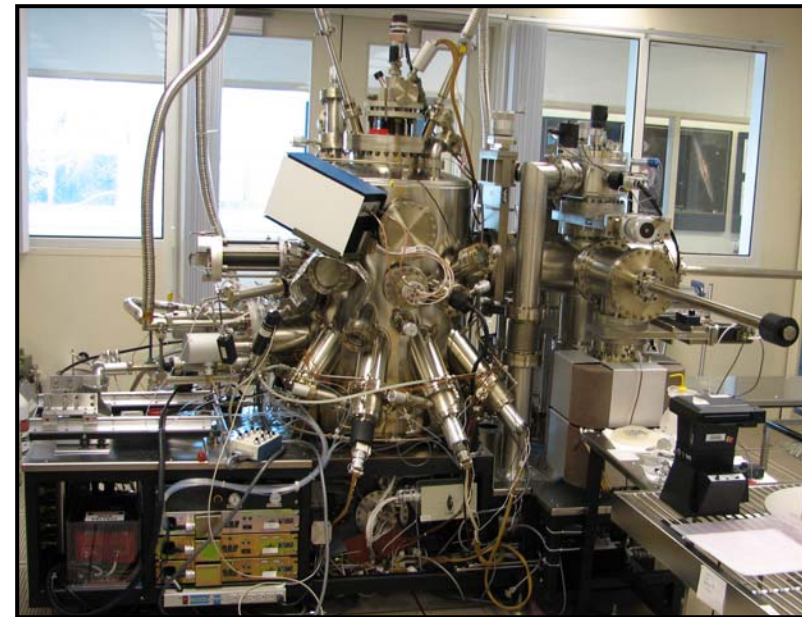
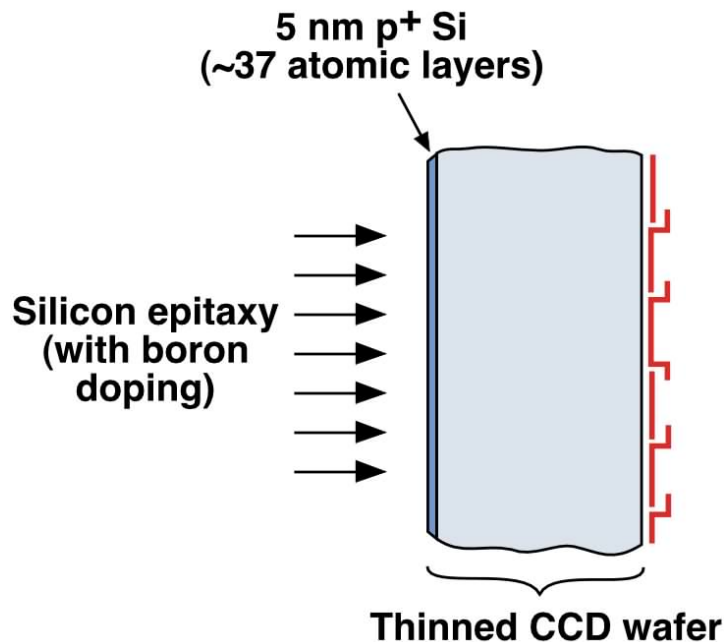
- **UV (<400 nm) is challenging**
  - Shallow penetration depth of radiation
  - Requires extremely thin, doped surface layer
- **Demonstrated near 100% internal quantum efficiency, temporally stable**
- **Applicable to improved soft-x-ray response below 500 eV**





# Molecular Beam Epitaxy Backside Treatment

- Fully processed imager wafers are chemically thinned to typically 40-50 $\mu$ m
- Grow 5nm of p+ Si epitaxially on the back surface at  $\sim 430^{\circ}\text{C}$ 
  - Epitaxially doped layer  $\ll$  absorption length
  - Absorption length  $< 10$  nm at  $\lambda = 200\text{-}350$  nm



Ultra-high-vacuum molecular-beam epitaxy system



# Lincoln Microelectronics Laboratory



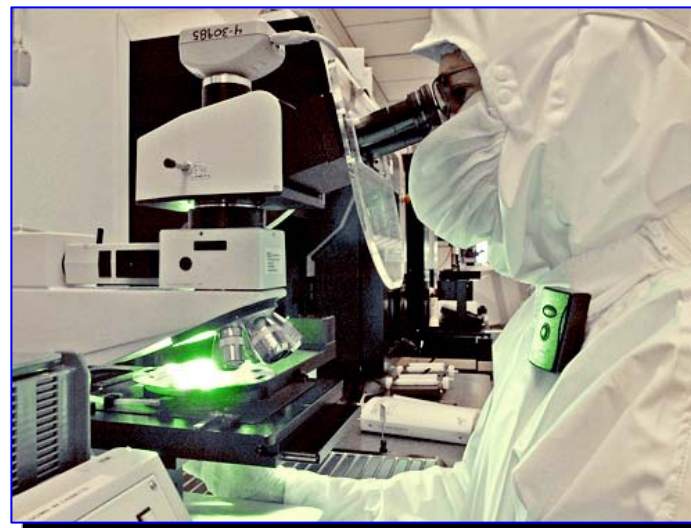
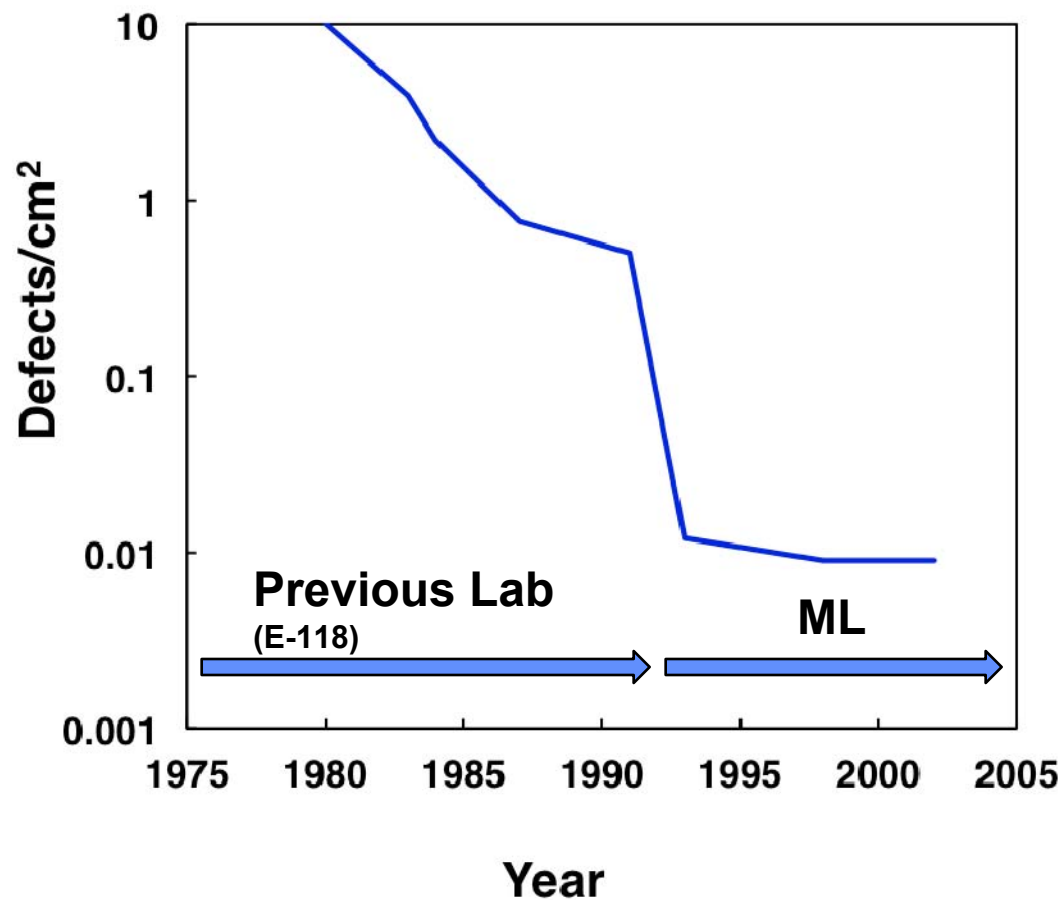
**70,000 ft<sup>2</sup> total:  
8,100 ft<sup>2</sup> class 10; 10,000 ft<sup>2</sup> class 100**

## Application Areas

- High performance CCD imagers
- Photon-counting APD arrays
- Low power silicon-on-insulator CMOS
- Rad-hard and space electronics
- Superconducting electronics
- Microelectromechanical RF/optical switches

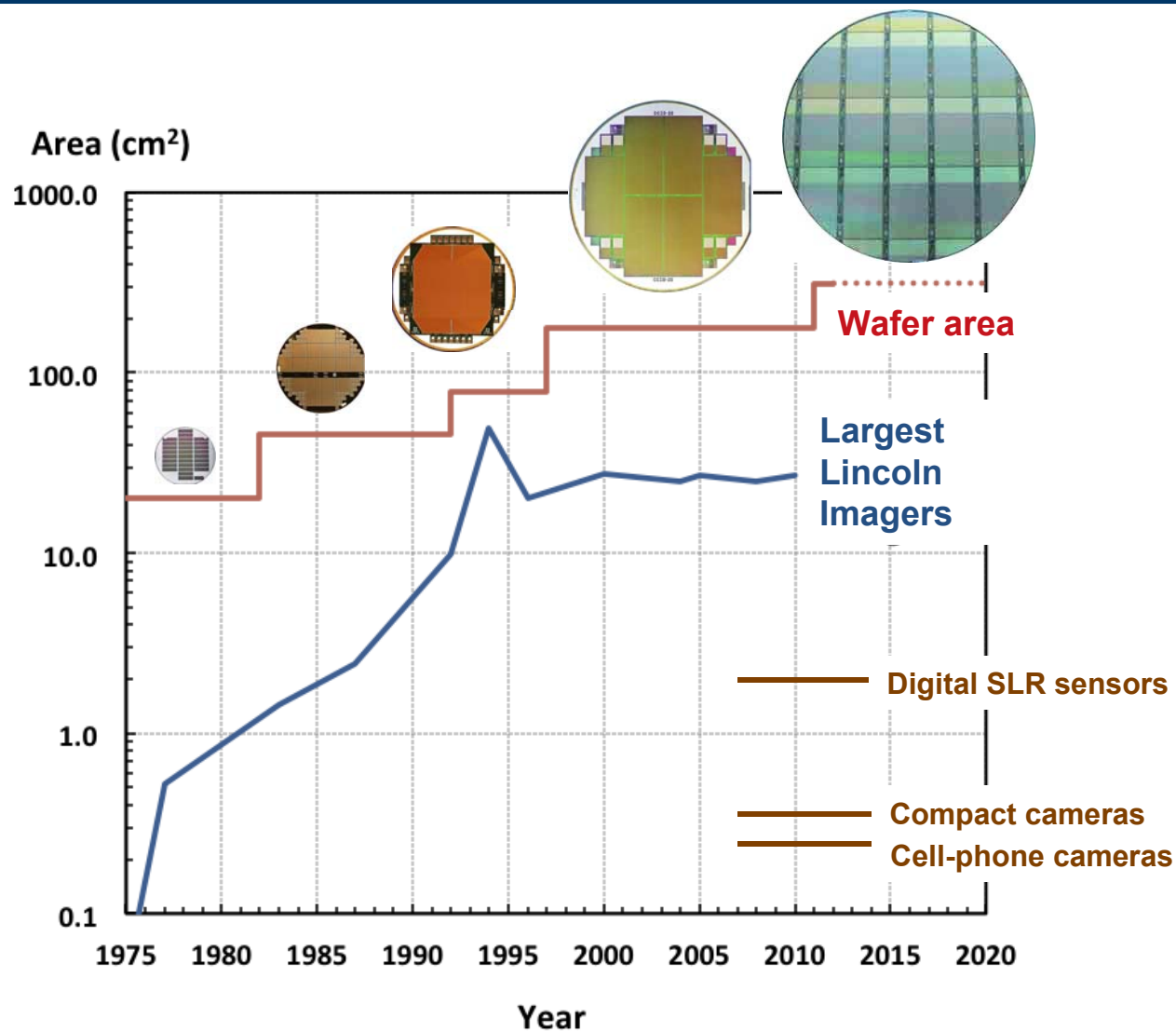


# Impact of the Microelectronics Lab





# Growth in Wafer and Device Sizes





# Pan-STARRS Mission

## (Panoramic Survey and Rapid Response System)

High-cadence, wide-field surveys for detection of asteroids and transient phenomena

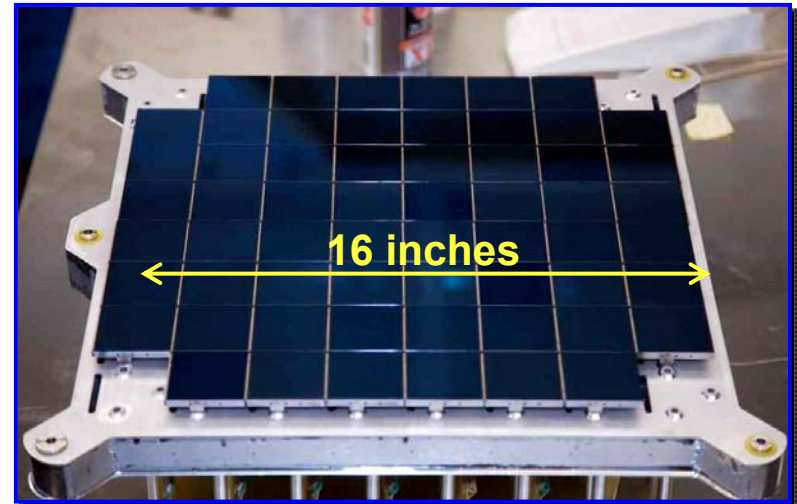
- Four, 1.8-m aperture telescopes
  - $m_v \sim 24$
  - 30-60 sec exposure
  - FOV: 3 degrees
  - Spatial sampling: 0.3 arcsec
  - Survey Mode: 6,000deg<sup>2</sup> /night





# Gigapixel Astronomy: Technology Goals

- **Goal 1: Build the largest and most cost effective astronomy CCD focal planes made**
  - Large CCD imager tiles
  - High yield
  - Redundant optics design
    - Allow for missing cells and seam loss
  
- **Goal 2: Remove translational atmospheric distortions (“de-twinkle”)**
  - Use Orthogonal CCD structure
  - Organize imager chip into independently operable Orthogonal Transfer CCD (OTCCD) cells

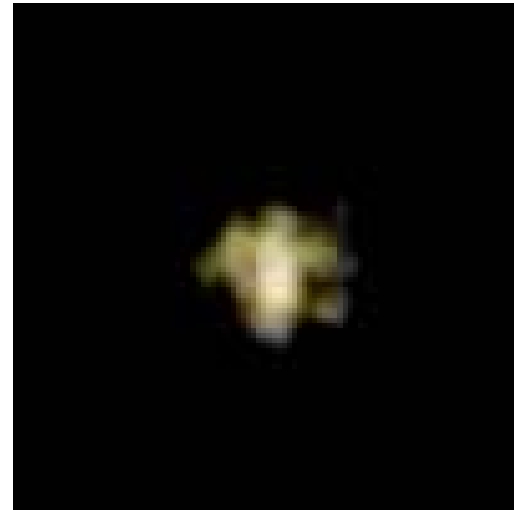
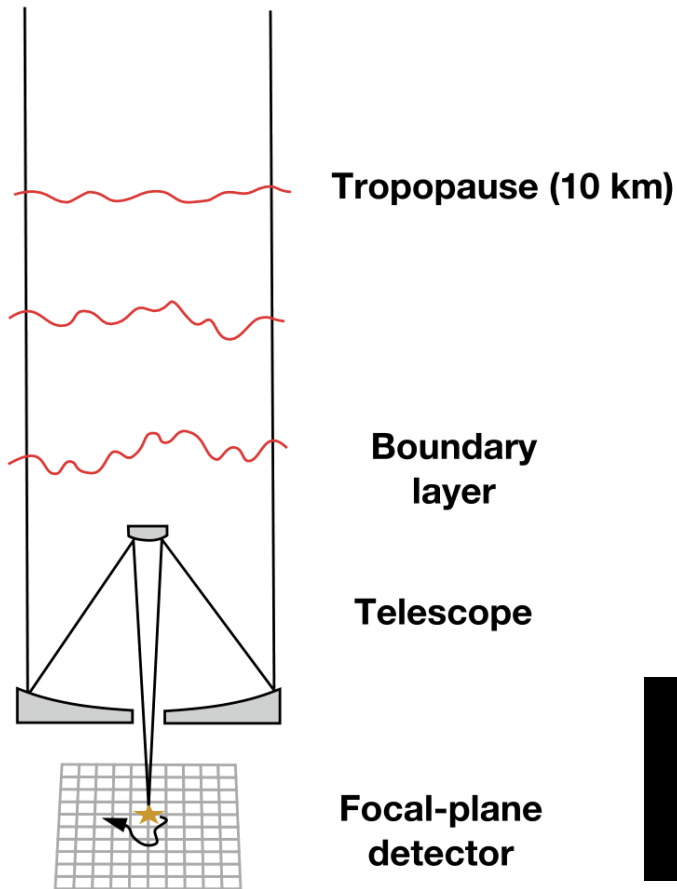




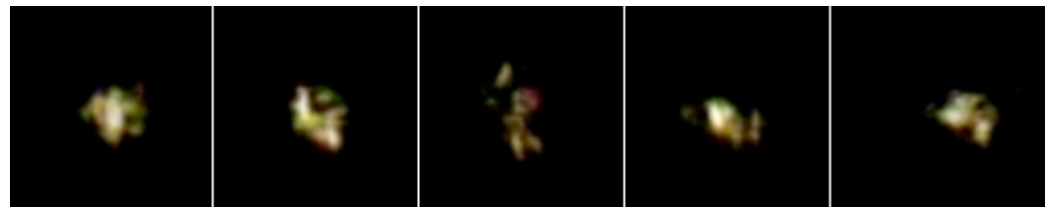


# Image Motion from Atmospheric Turbulence (de-Twinkle)

— Wavefront external  
— to earth's atmosphere



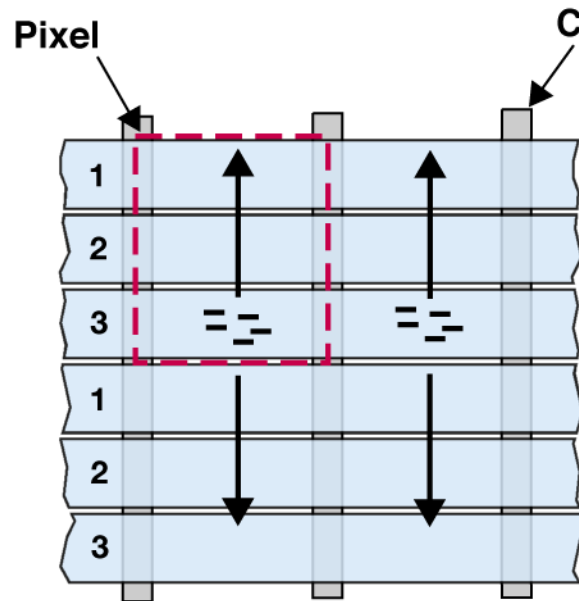
<http://www.noao.edu/education/gsm/seeing>



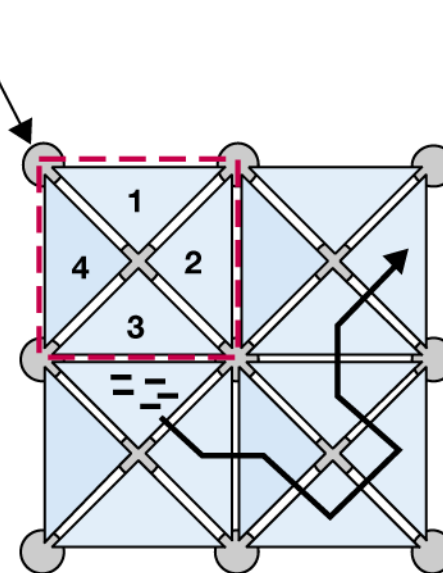


# 1995: Orthogonal Transfer CCD (OTCCD)

- Charge transfer in arbitrary directions
- Can noiselessly remove blur due to scene or platform motion
  - Ground-based astronomy (atmospheric effects)
  - Imaging from unstable platforms (e.g., satellites)



**Conventional CCD: charge transfer in two directions**

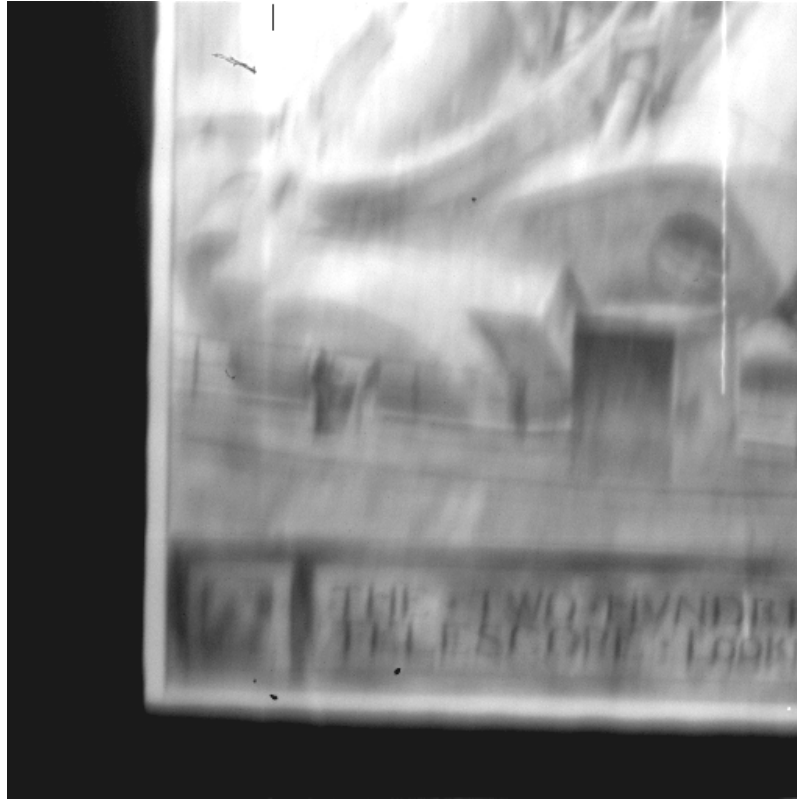


**OTCCD: charge transfer in all directions**



# Laboratory Demo of Motion Compensation

CCD camera spring mounted



OTCCD gates fixed during image acquisition



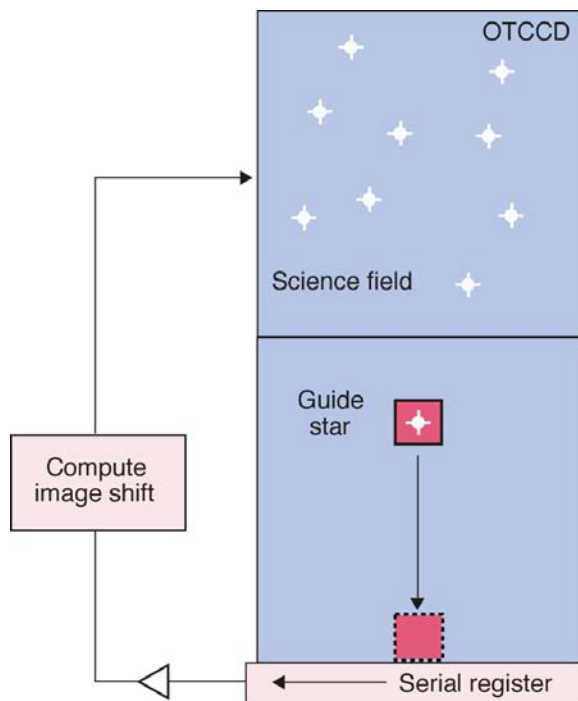
OTCCD gates tracking image motion



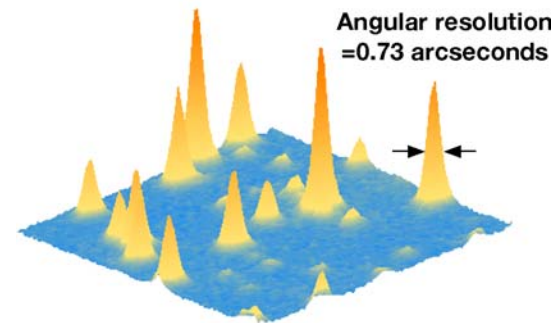
# 1997: Application of OTCCDs in Astronomy

- **Electronic image-motion compensation**

- Wavefront distortion (electronic tip/tilt correction)
- Telescope shake

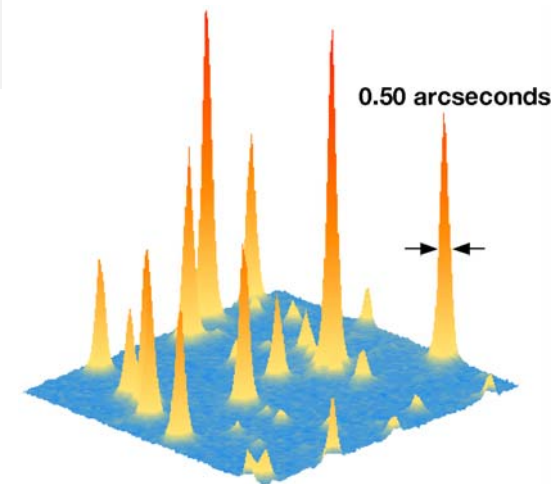


## Star-cluster imagery (M71)



No motion compensation

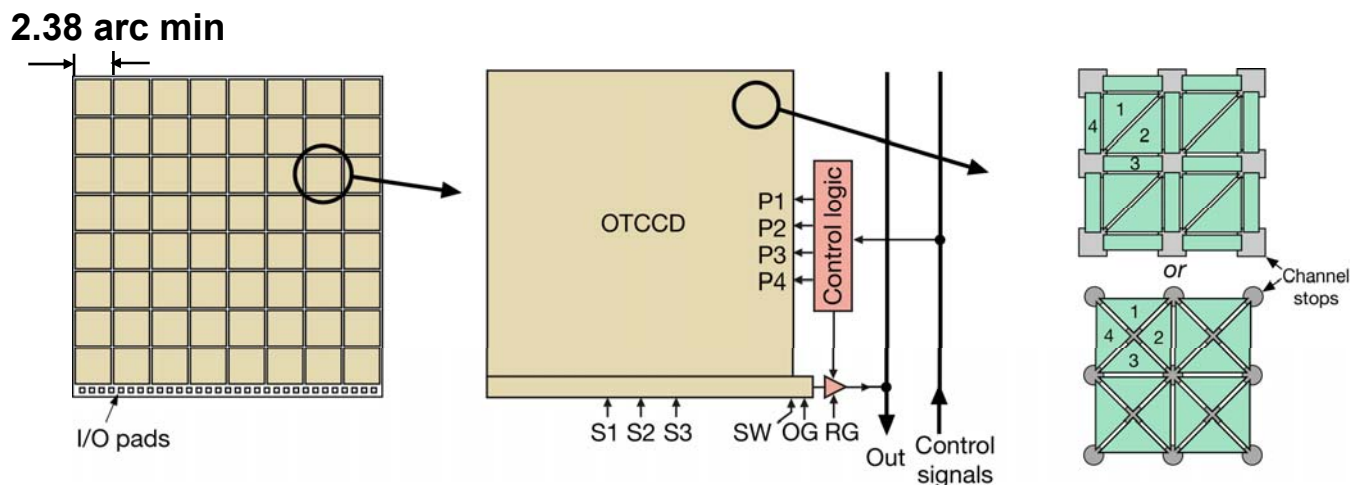
SNR increase:  
1.7x



With motion compensation



# Orthogonal Transfer Array



**OTA: 8×8 array of OTCCD cells**

**OTA cell with I/O control**

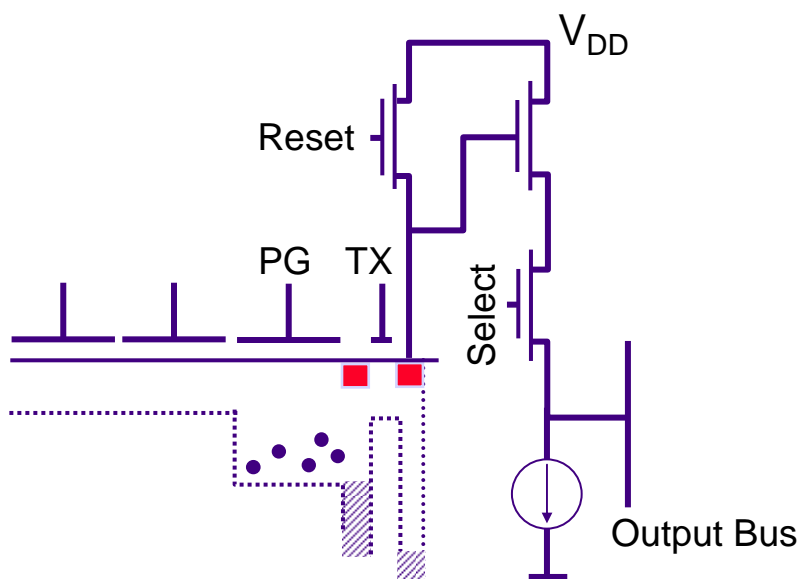
**Four-phase OTCCD pixels**

- **New device paradigm**
  - 2D array of independent OTCCDs
  - Independent clocking and readout of OTCCDs
- **Advantages**
  - Enables spatially varying image motion correction
  - Isolated defective cells tolerable (higher yield)



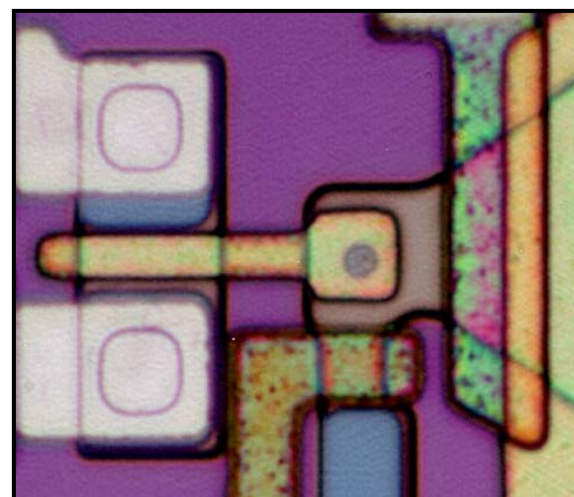
# Charge Sensing

- **Similar techniques for achieving low noise in CCD or CMOS sensors**
  - **Minimize sense node capacitance**
  - **Minimize sense FET noise voltage**
  - **Employ correlated double sampling to correct for reset noise**



PG = Photogate  
TX = Transfer gate

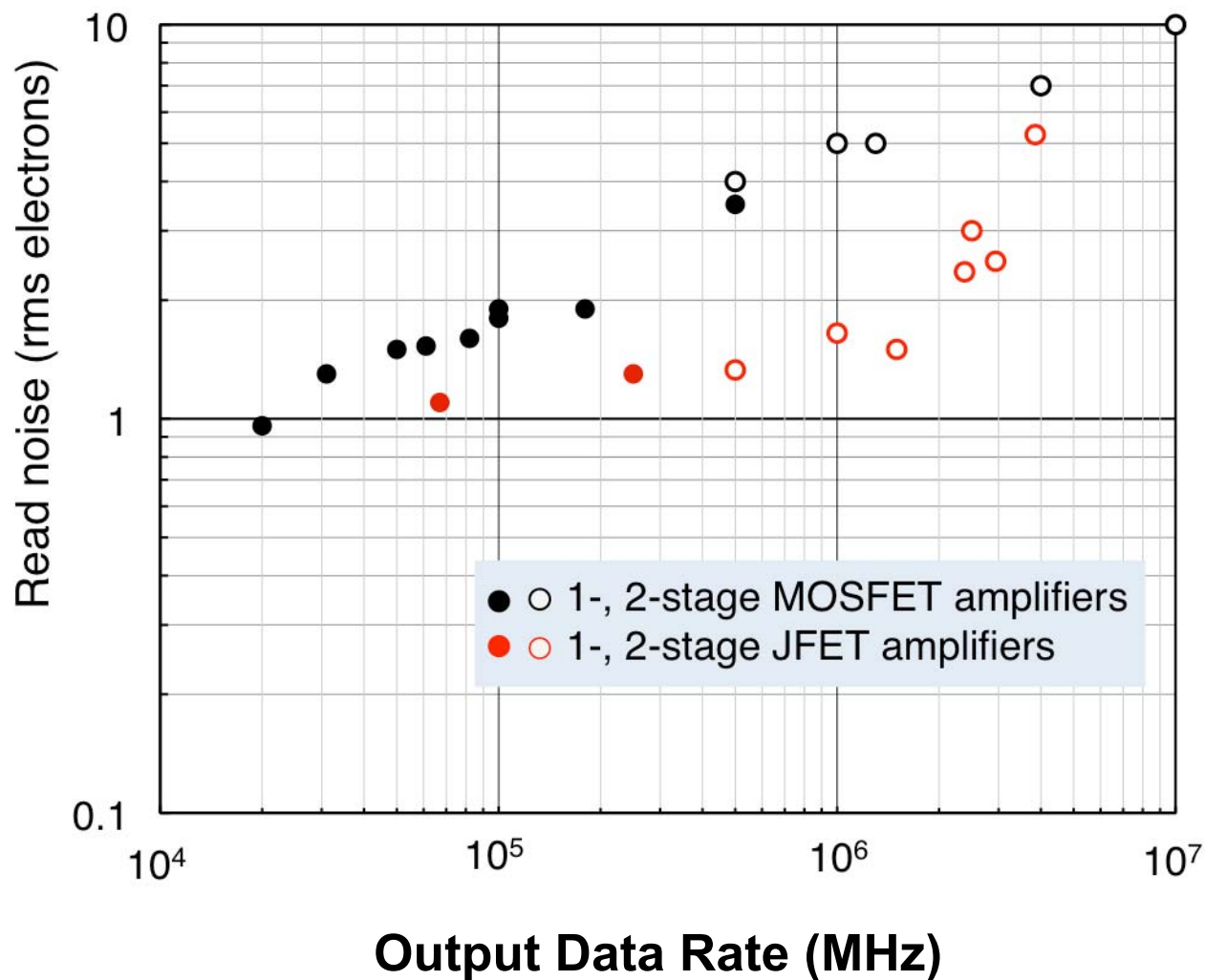
## Charge-sensing Amplifier



Sense-node Capacitance  $\sim 5$  fF  
( $20 \mu\text{V}/e^-$ )



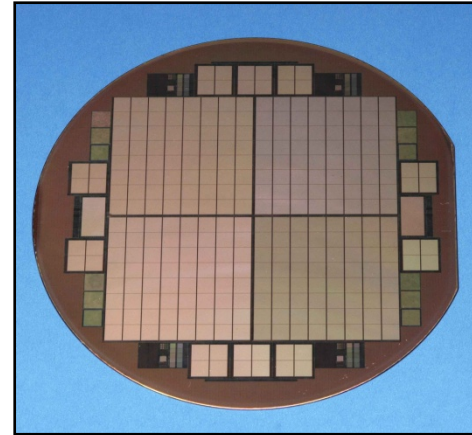
# Comparison of MOSFET and pJFET-based Output Circuits





# Device Fabrication and Sample Imagery

- Four OTAs on 150-mm wafer (die size 49.5×50.1 mm)
- Four-poly, n-buried-channel process
- Fabricated on 5,000  $\Omega$ -cm float-zone silicon wafers
- Back-illuminated devices thinned to 75  $\mu\text{m}$



150-mm wafer with four OTAs



Image from back-illuminated OTA  
10- $\mu\text{m}$  pixel, 22.6 Mpixels

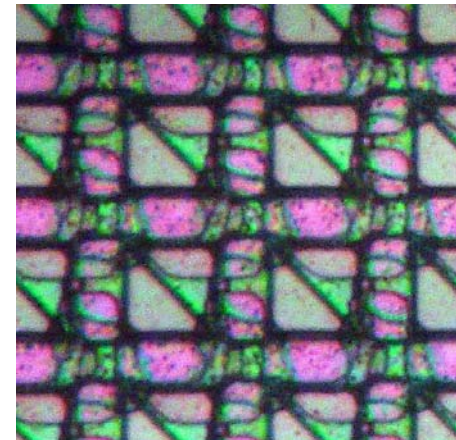


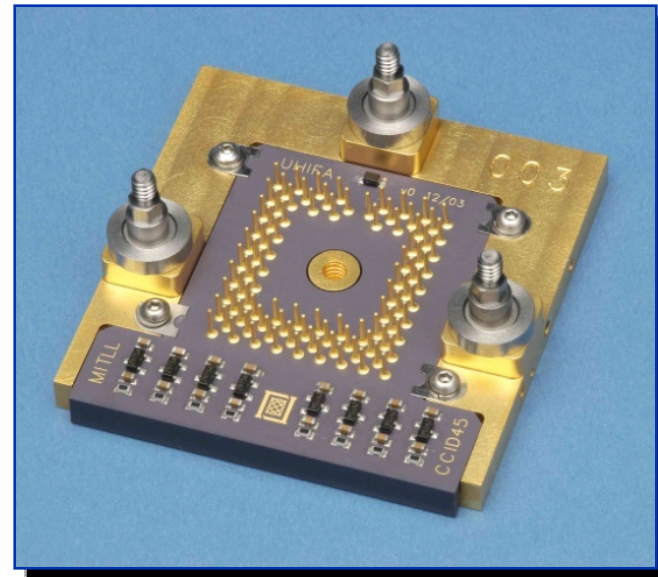
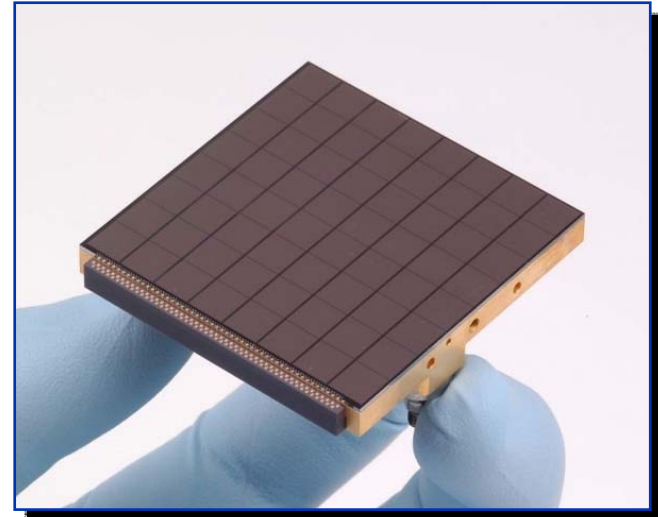
Photo of pixel array





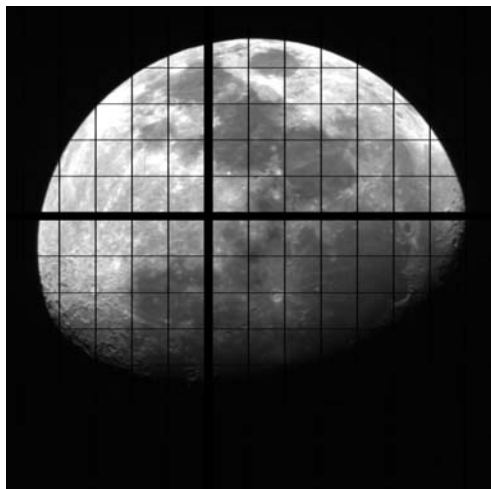
# Very large focal plane arrays: Packaging requirements

- Large number (60) of chips
- Minimal seam loss
  - Four-side abutable
  - Repairable
- Array flatness ( $\pm 20$  microns) under cryogenic operation
- Low noise operation
  - Good electrical isolation
- Moderate wire count

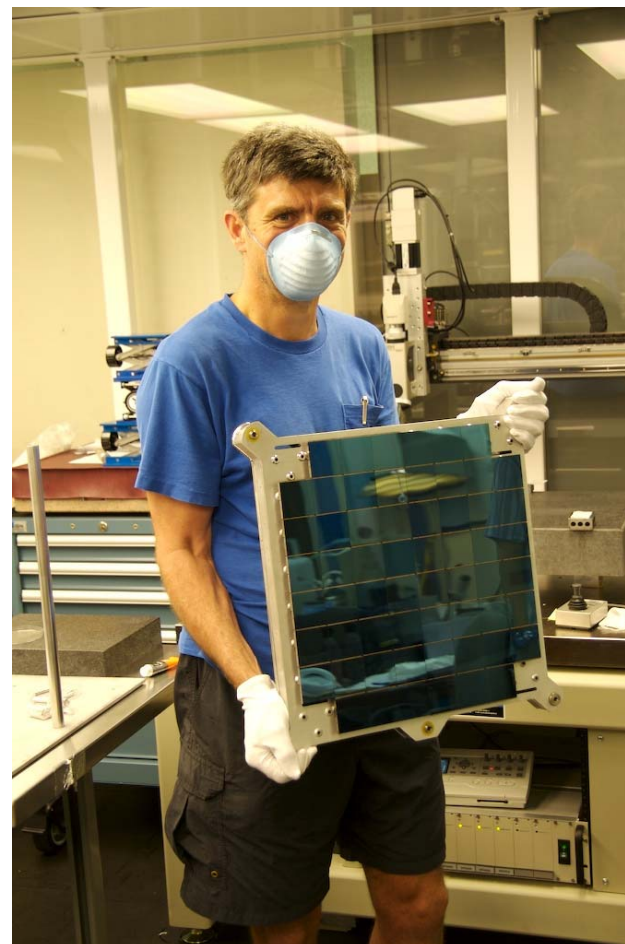




# Pan-STARRS Gigapixel Camera



**Images from first light  
(August 2007)**

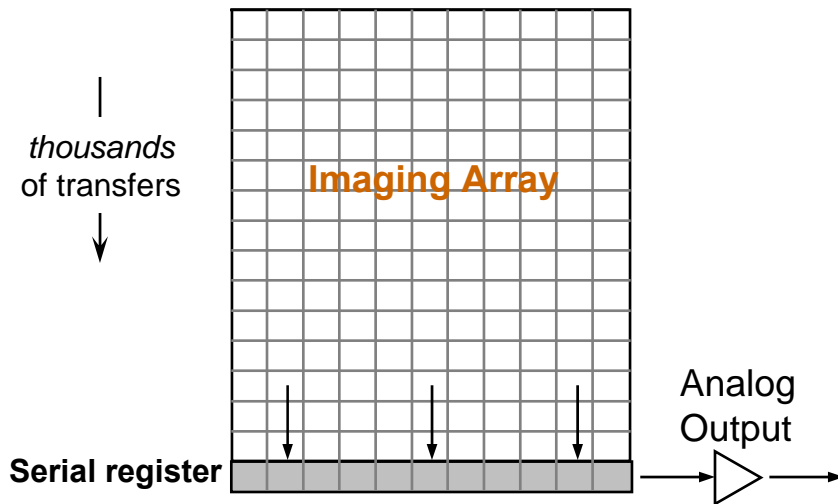


**60 OTAs; 1.36 Gpixels**



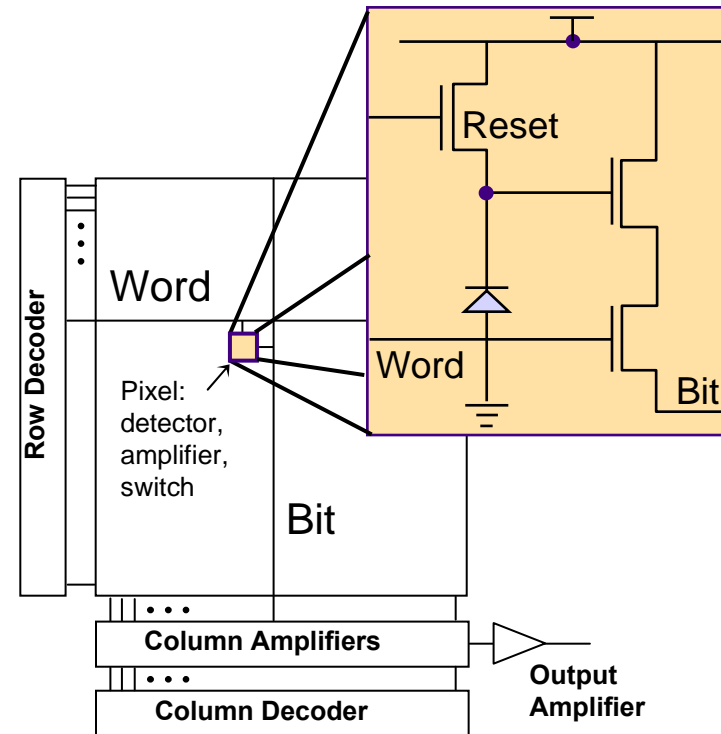
# Comparison of CCD and CMOS Imagers

## CCD imager



- **Pros**
  - Still used in highest performance applications
  - Best QE, lowest noise
- **Cons**
  - Sensitive to proton damage in space applications

## CMOS Active Pixel Sensor (APS)

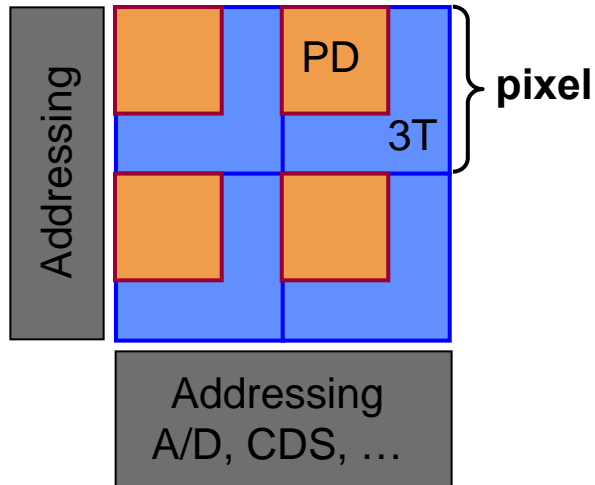


- **Pros**
  - Provides on-chip electronics
- **Cons**
  - Modest imaging performance for monolithic



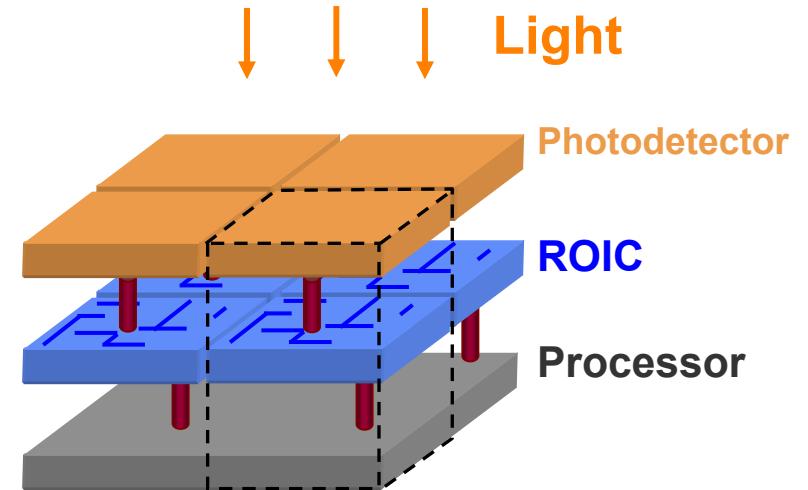
# Four-Side Abutable 3-D CMOS Image Sensor Development

## Conventional Monolithic CMOS Image Sensor



- Pixel electronics and detectors share area
- Fill factor loss
- Co-optimized fabrication
- Control and support electronics placed outside of imaging area

## 3-D Pixel



- 100% fill factor detector
- Fabrication optimized by layer function
- Local image processing
  - Power and noise management
- Scalable to large-area focal planes

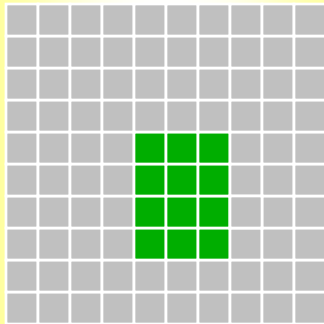


# Special Scanning Techniques Supported by CMOS

- Different scanning methods are available to reduce the number of pixels being read:
  - Allows for higher frame rate or lower pixel rate (reduction in noise)
  - Can reduce power consumption due to reduced data

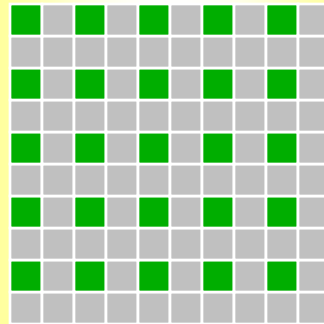
## Windowing

- Reading of one or multiple rectangular subwindows
- Used to achieve higher frame rates (e.g. AO, guiding)



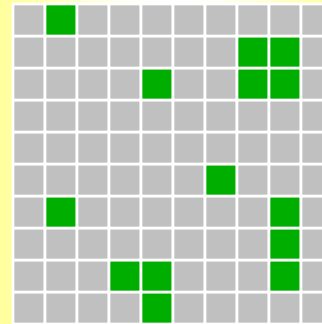
## Subsampling

- Skipping of certain pixels/rows when reading the array
- Used to obtain higher frame rates on full-field images



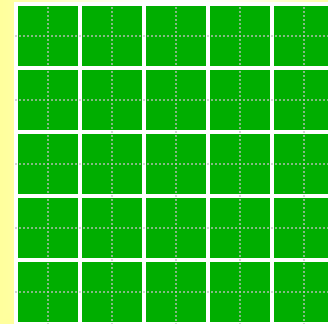
## Random Read

- Random access (read or reset) of certain pixels
- Selective reset of saturated pixels
- Fast reads of selected pixels



## Binning\*

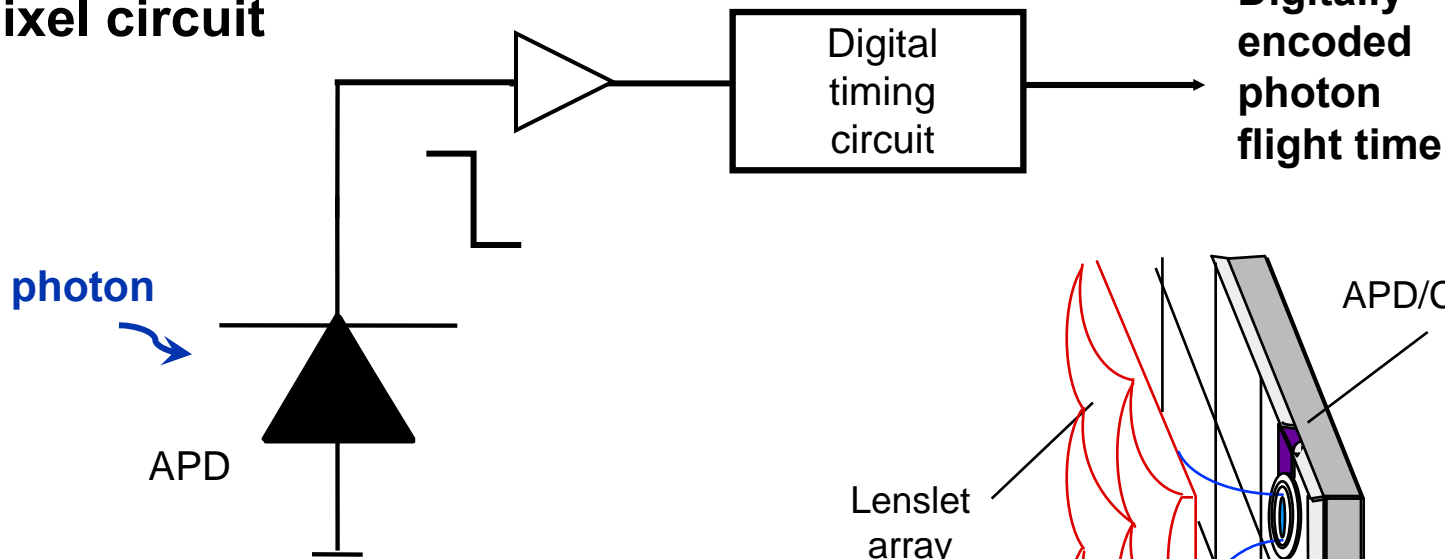
- Combining several pixels into larger super pixels
- Used to achieve lower noise and higher frame rates



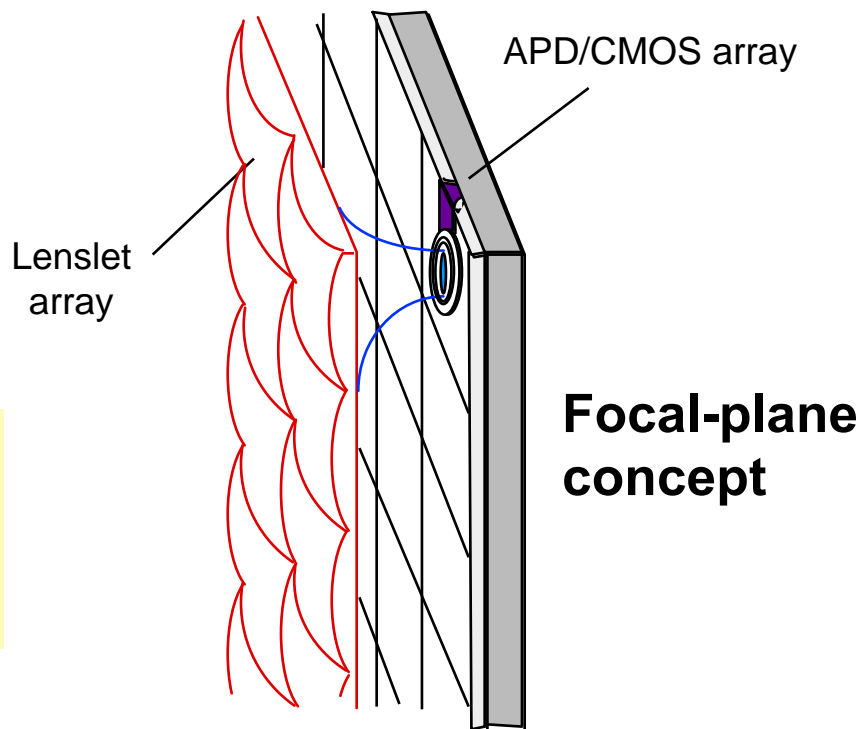


# Geiger-Mode Imager: Photon-to-Digital Conversion

**Pixel circuit**

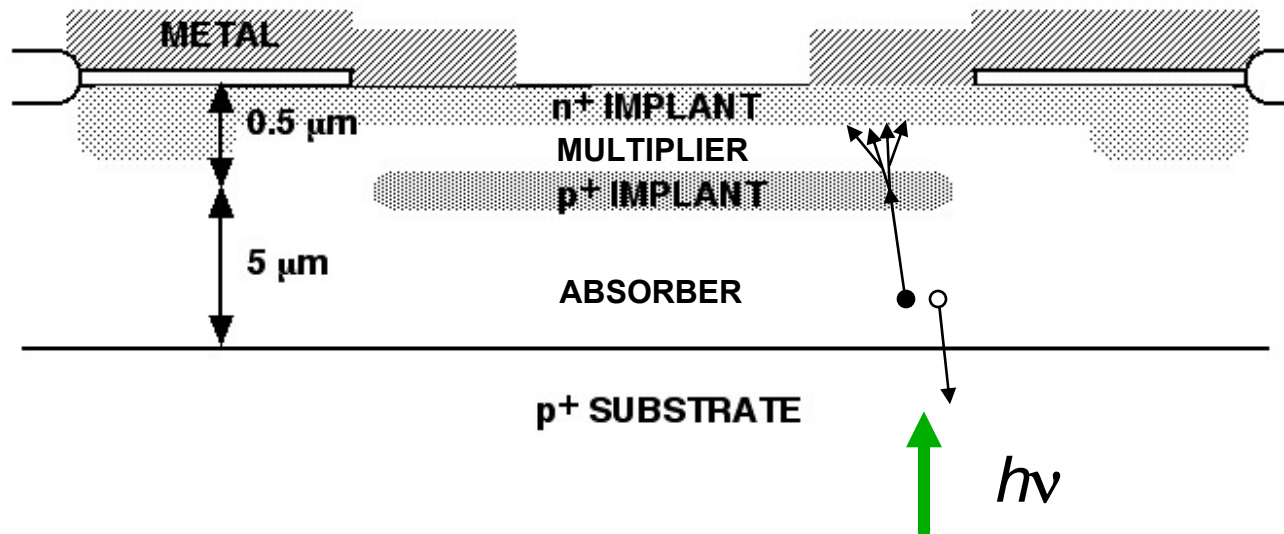


**Quantum-limited sensitivity**  
**Noiseless readout**  
**Photon counting or timing**



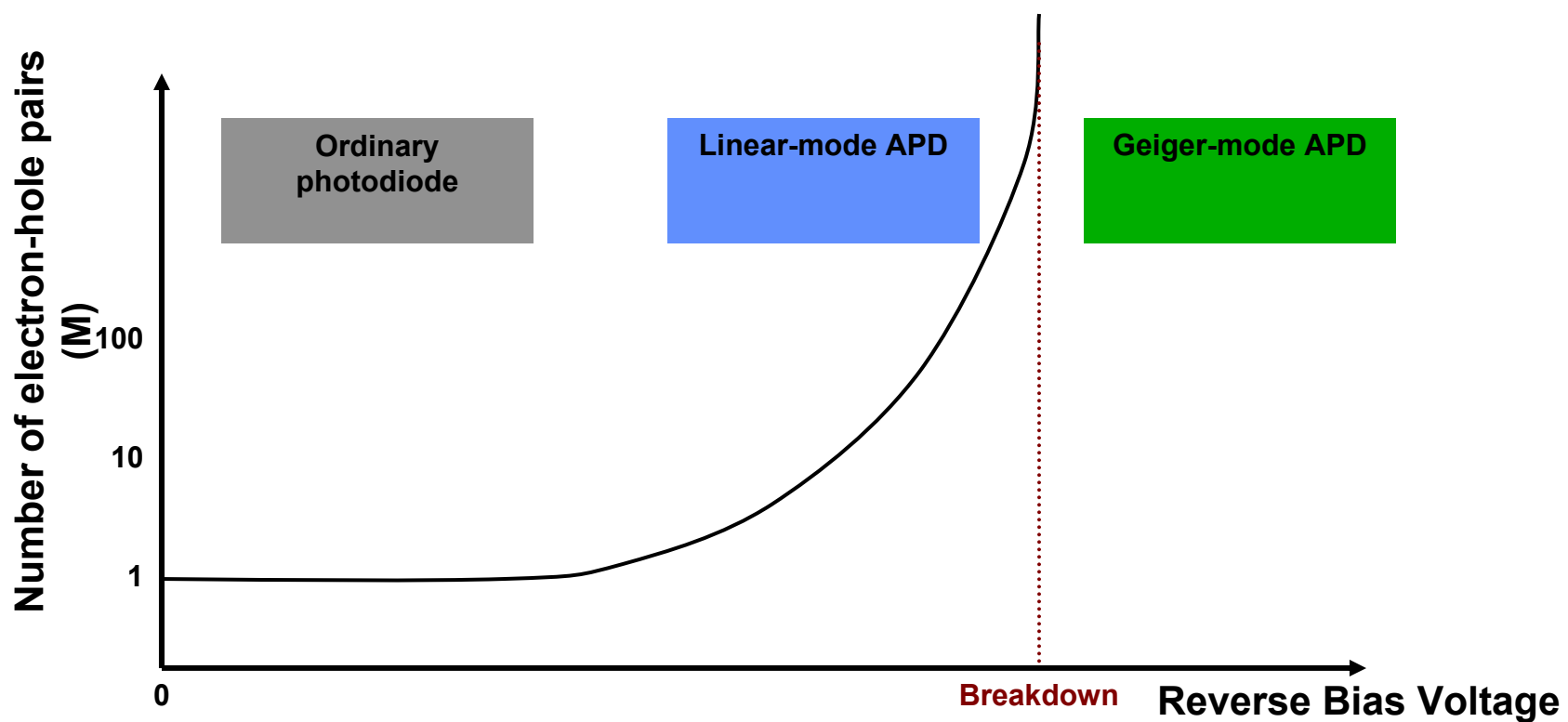


# APD Structure and Operation



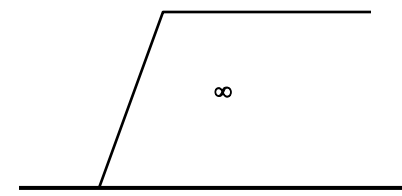
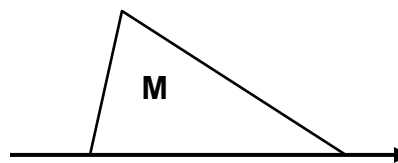
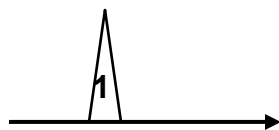


# Gain of an APD



Current vs time after one photon

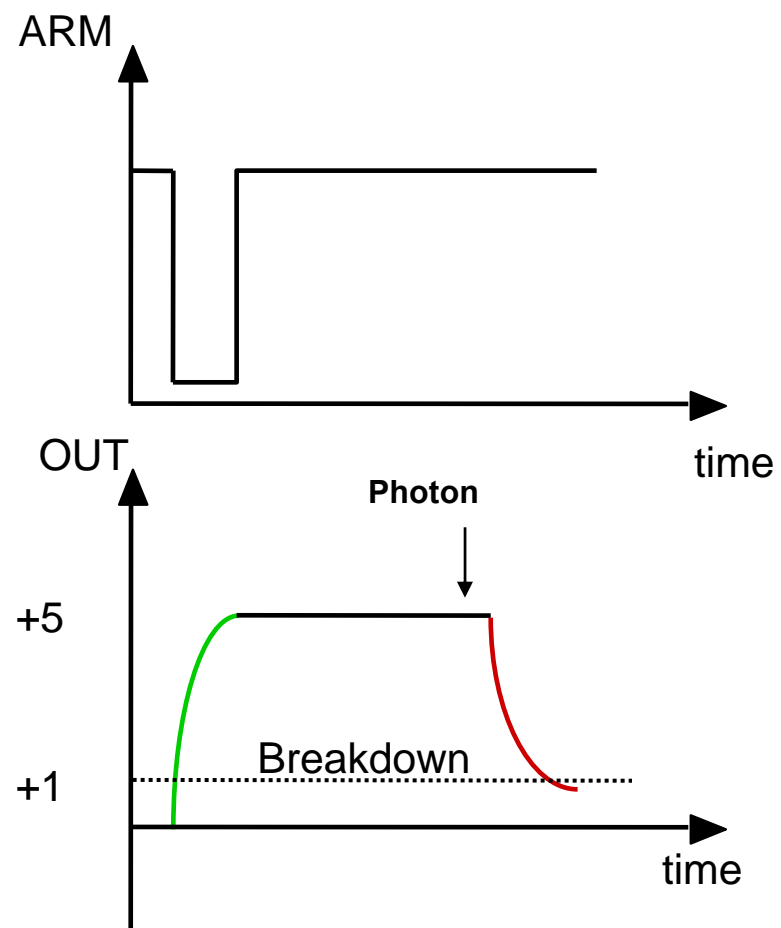
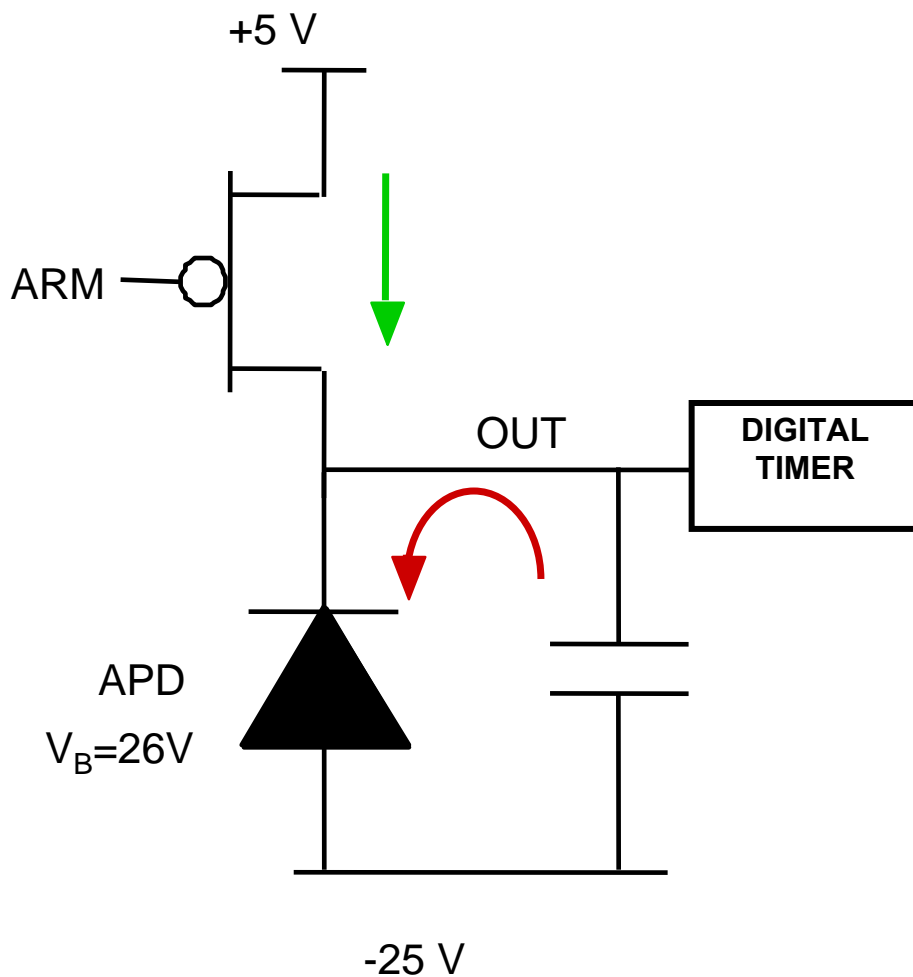
$I(t)$





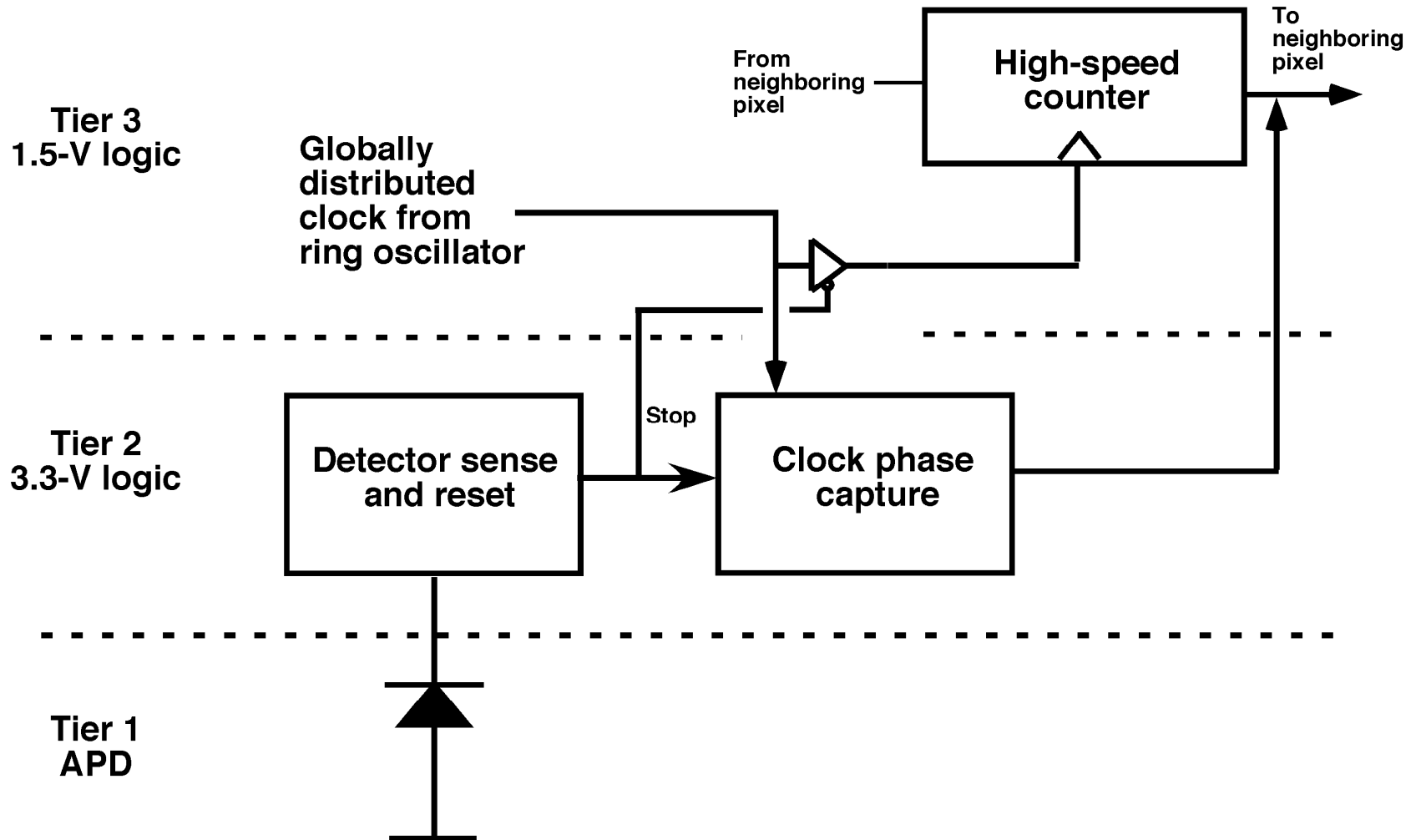


# Reset and Quenching



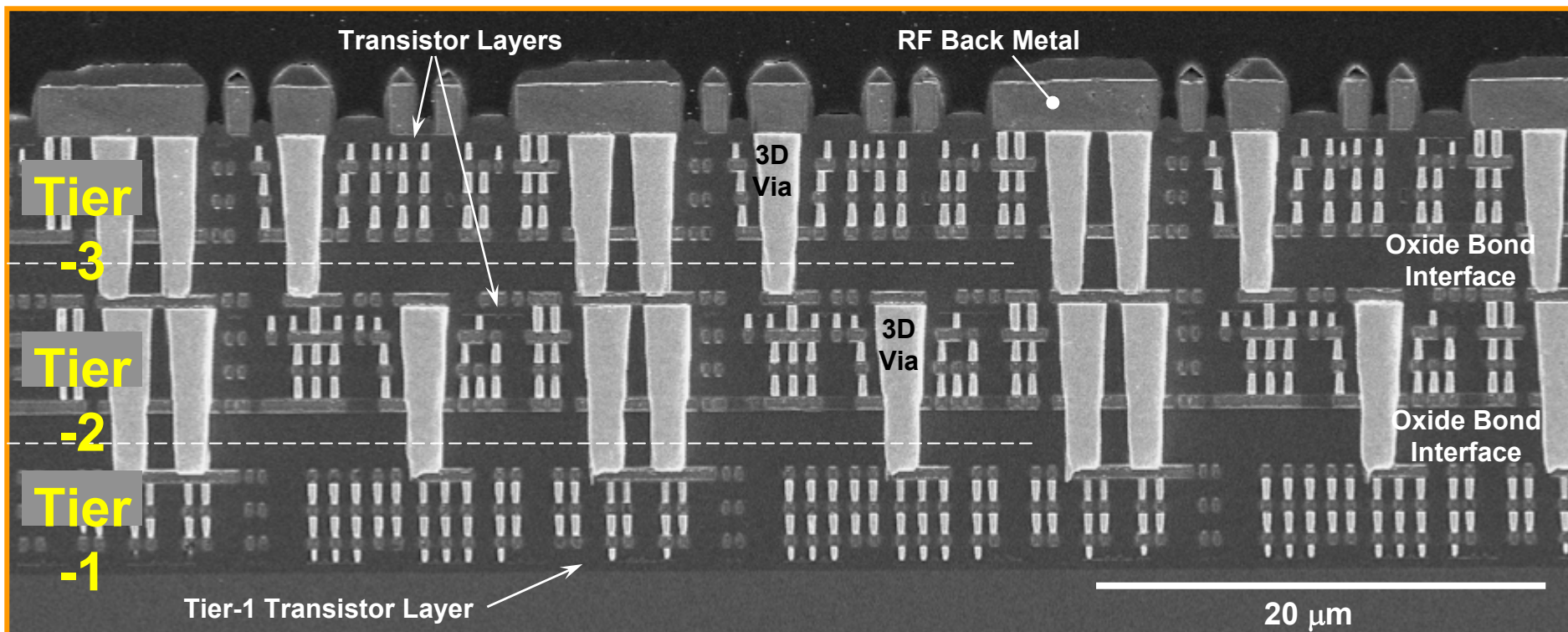


# Pixel Block Diagram





# 3-Tier 3DIC Cross-Section



**Three FDSOI CMOS Tiers, total active circuit height ~ 21  $\mu\text{m}$**

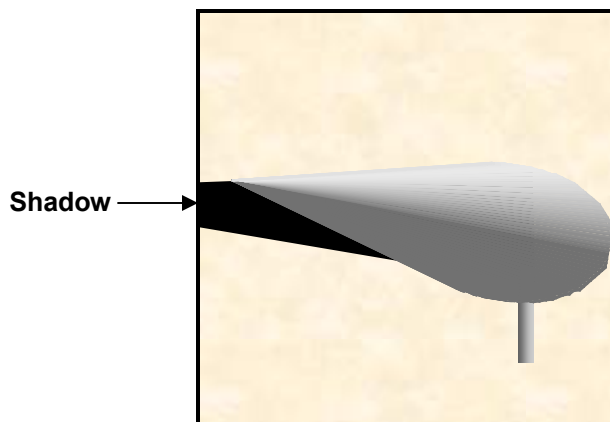
**Tier 1 bottom, Tier 2 and Tier 3 inverted and bonded on top, substrates removed**

**11 metal interconnect layers thick RF top metal**

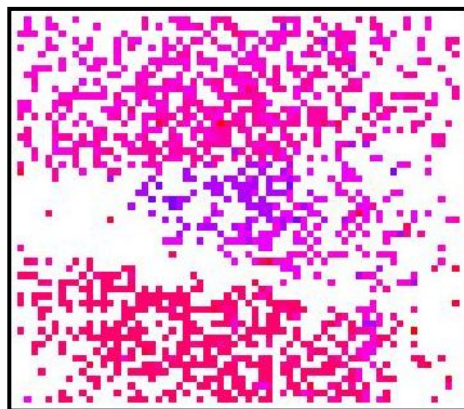
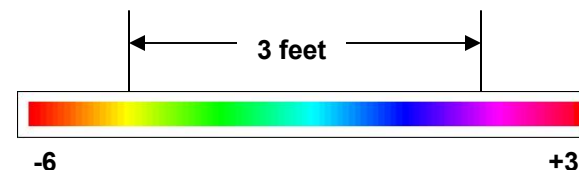
**Dense unrestricted 3D vias for electrical connections between tiers**



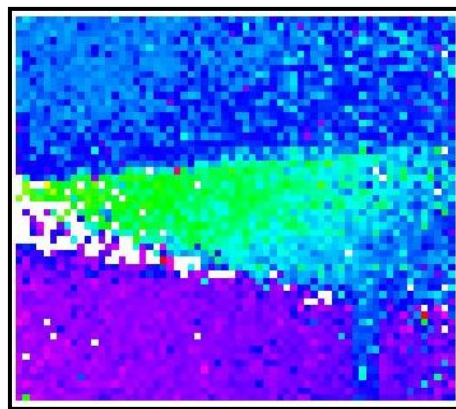
# Example of Multiframe Processing



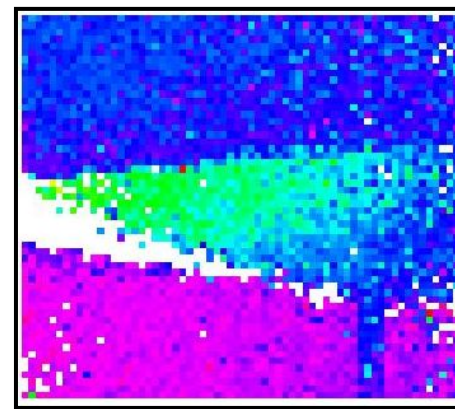
Target:  
Cone and Support Post  
In Front of Flat Plate



Each frame is filtered to eliminate out-of-range values. Then frame-to-frame jitter is measured and subtracted out using average timing value over the top ten rows.



21 frames combined by averaging the timing value for each pixel



10 of these 21-frame averages are combined by picking the most common timing value at each pixel (mainly eliminates spurious counts)



# Summary

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- **CCD imagers continue to demonstrate the highest performance for large-format, broad spectral response, scientific applications**
  - Leverage enormous investment in silicon-based microelectronics
- **CMOS technology can bring many attractive features to astronomical detectors via 3D integration**
  - Gm-APDs for Quantum-limited sensitivity
  - Pixel-level digitization and noiseless readout
- **Continued and desired improvements**
  - Higher data rates without a noise penalty
  - Flexible readout modes with electronic shuttering
  - On-chip computation and data thinning
  - Design for yield
- **Will we soon enter the era of smaller, smarter telescopes?**